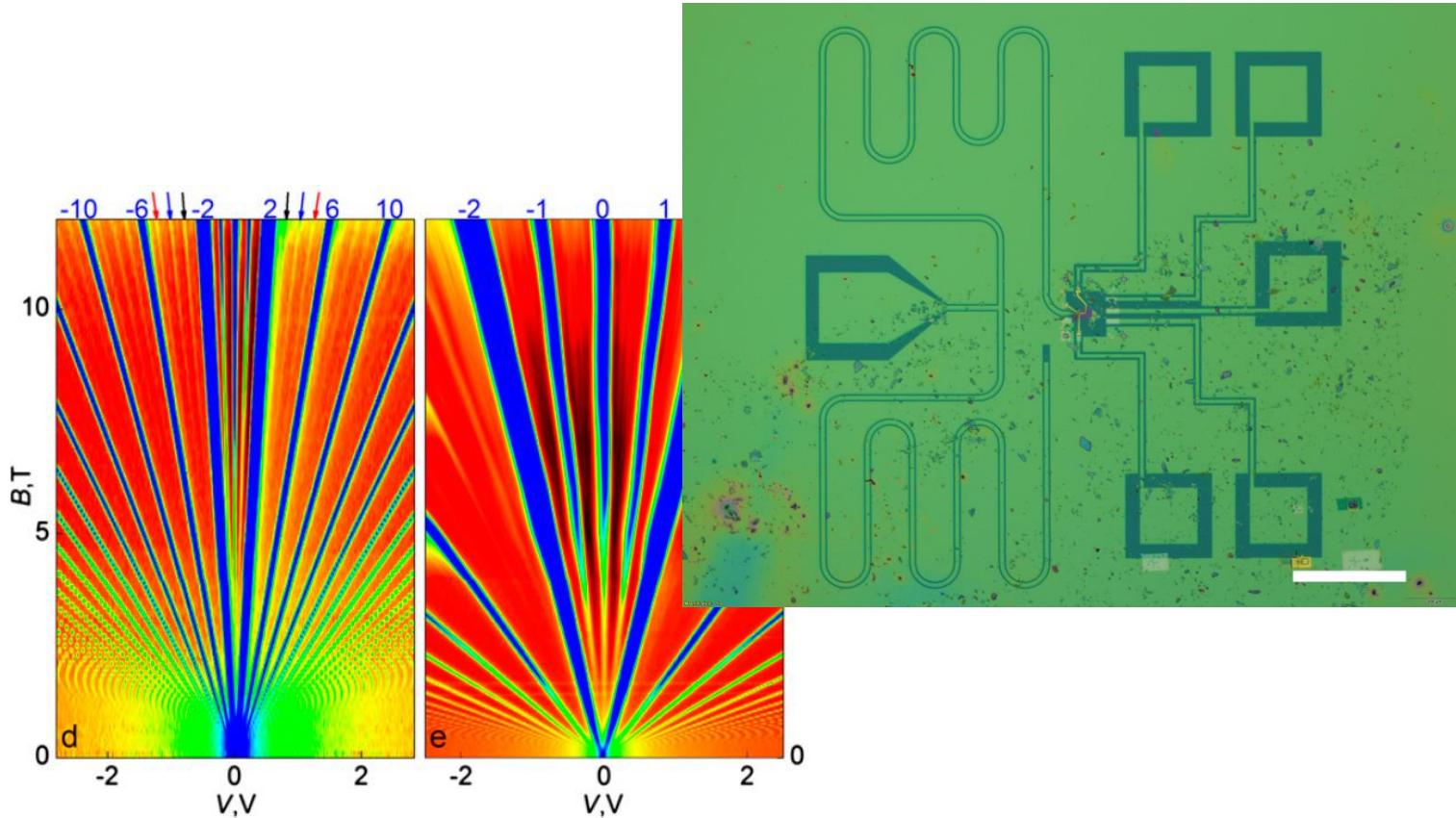
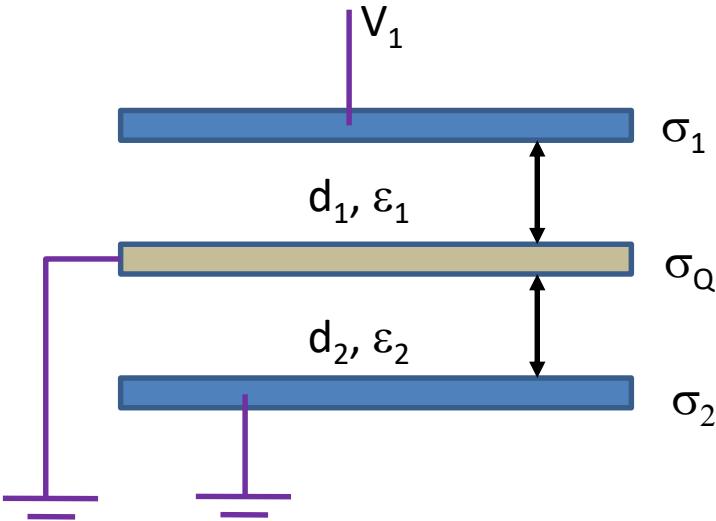


Quantum Capacitance

Budapest University of Technology and Economics 2019 spring



Quantum Capacitance – Double layer



$$C_i = \frac{\epsilon_i}{4\pi d_i}, \quad i = 1, 2$$

$$\sigma_1 + \sigma_2 + \sigma_Q = 0$$

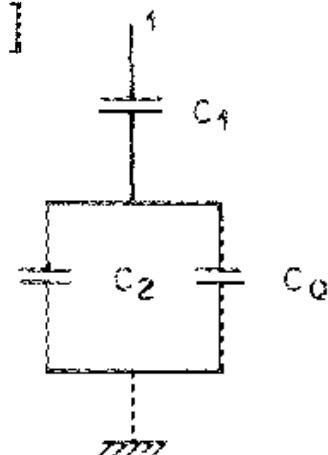
$$\sigma_2 = -\sigma_1 \sin^2(\phi),$$

$$\sigma_Q = -\sigma_1 \cos^2(\phi)$$

$$\tan^2(\phi) = \hbar^2 \epsilon_2 / 4mg_v d_2 e^2 \equiv C_2/C_Q$$

$$C_Q = \frac{g_v m e^2}{\pi \hbar^2} \quad \hbar \rightarrow 0, C_Q \rightarrow \infty$$

$$\sigma_2 = -\sigma_1 [C_2/(C_2 + C_Q)]$$



Energy terms:

Electrostatic

$$E_i = \int_0^{d_i} \frac{\epsilon_i F_i^2 dx}{8\pi} = \frac{2\pi d_i \sigma_i^2}{\epsilon_i}, \quad i = 1, 2,$$

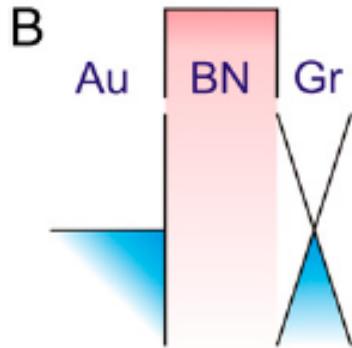
$$F_1 = 4\pi\sigma_1/\epsilon_1 \text{ and } F_2 = -4\pi\sigma_2/\epsilon_2$$

Kinetic

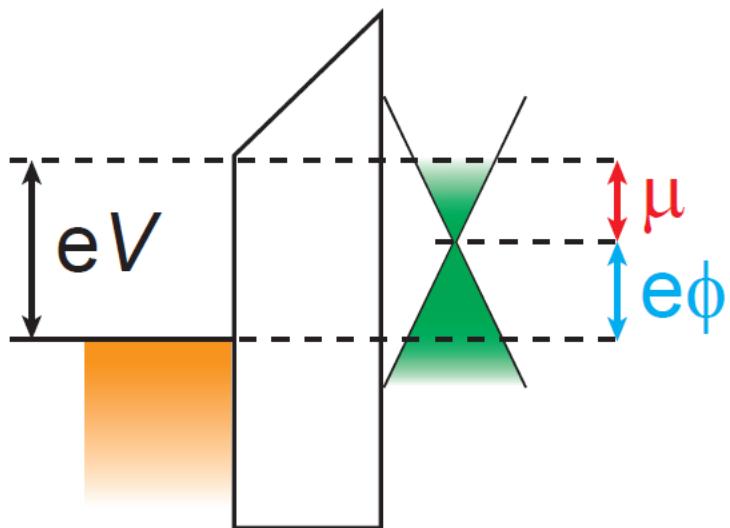
$$E_Q = \pi \hbar^2 \sigma_Q^2 / 2g_v m e^2$$

$$\delta E_{\text{tot}}(\phi) = 0$$

Quantum Capacitance – Coupling to an electrode



2D material coupled to tunnel barrier
via tunnel barrier



$$eV = e\phi + \mu$$

$$\frac{dV}{dQ} = \frac{d\phi}{dQ} + \frac{1}{Ae^2} \frac{d\mu}{dn}$$

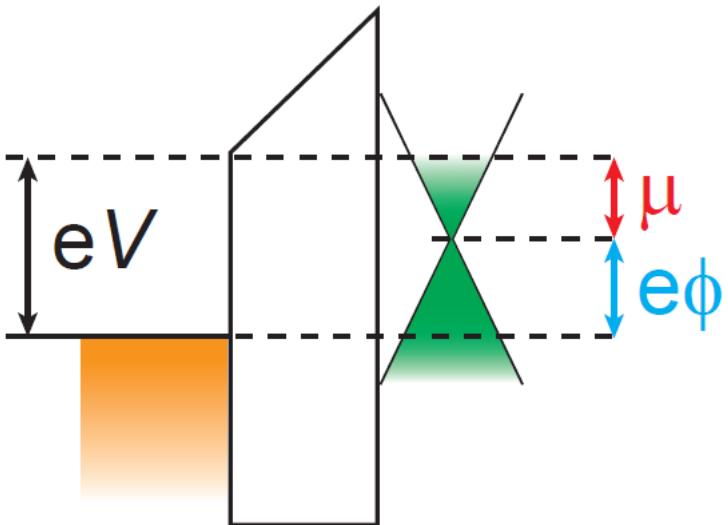
$$\frac{1}{C} = \frac{1}{C_g} + \frac{1}{C_q}$$



Geometric
capacitance



Quantum
Capacitance
 $= e^2 \cdot DOS = e^2 \cdot D_0$

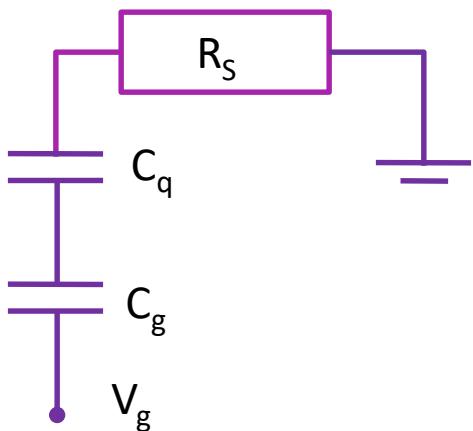


$$eV = e\phi + \mu$$

$$\frac{dV}{dQ} = \frac{d\phi}{dQ} + \frac{1}{Ae^2} \frac{d\mu}{dn}$$

$$\frac{1}{C} = \frac{1}{C_g} + \frac{1}{C_q}$$

$$n = \frac{C_Q C_G}{C_Q + C_G} V_G$$



For a metal: $C_q \gg C_g$, Fermi level does not move
 $n = C_G V_G$

For a low DOS: $C_q \ll C_g$, Fermi level moves substantially
 $n = C_Q V_G$

Finite temperature:

$$C_Q = e^2 \int_{-\infty}^{+\infty} D(E) \left(-\frac{\partial f(E-E_F)}{\partial E} \right) dE$$

Quantum Capacitance

$$E = -qV_g + U_0(N - N_0)$$

$$\frac{\partial E}{\partial(-qV_g)} = 1 + \frac{U_0 \partial N}{\partial(-qV_g)} =$$

$$= 1 + U_0 \underbrace{\frac{\partial N}{\partial E} \frac{\partial E}{\partial(-qV_g)}}_{-D_0}$$

$$\frac{\partial E}{\partial(-qV_g)} = \frac{1}{1 + D_0 U_0}$$

using $U_0 = q^2/C_E$

$$\frac{\partial E}{\partial(-qV_g)} = \frac{1}{1 + \frac{C_q}{q^2} \frac{q^2}{C_E}} = \frac{1}{1 + \frac{C_q}{C_E}} = \frac{C_E}{C_0 + C_q}$$

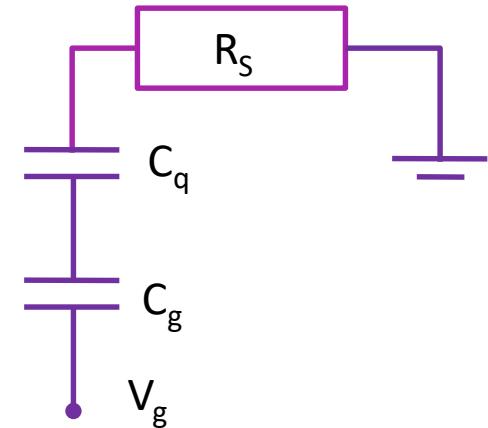
$D_0 \gg 1$

Large DOS, Coulomb term dominates

$$\frac{dE}{d(-qV_g)} = \frac{C_G}{C_q}$$

This is the naïve picture one would use for graphene:
 calculate from C_g the density and than calculate E_f using
 the DOS of graphene

Not for a metal $C_q \rightarrow \infty$, E_f does not move



$D_0 \ll 1$

Small DOS, Quantum capacitance dominates

$$\frac{dE}{d(-qV_g)} = 1 - C_q/C_G \quad \text{extreme case: gapped system} - C_q=0$$

Screening

$$\mathcal{H} = \sum_{\mathbf{k}\sigma} \varepsilon_{\mathbf{k}\sigma} c_{\mathbf{k}\sigma}^\dagger c_{\mathbf{k}\sigma} + \frac{1}{2V} \sum_{\substack{\mathbf{k}\mathbf{k}'\mathbf{q} \\ \sigma\sigma'}} U(\mathbf{q}) c_{\mathbf{k}+\mathbf{q}\sigma}^\dagger c_{\mathbf{k}'-\mathbf{q}\sigma'}^\dagger c_{\mathbf{k}'\sigma'} c_{\mathbf{k}\sigma}$$

General Hamiltonian:
Kinetic energy + Interaction

$$\rho(\mathbf{r}, t) = \rho_{\text{ext}}(\mathbf{r}, t) + \rho_{\text{ind}}(\mathbf{r}, t)$$

As a reaction to external perturbation: density rearrangement

$$\epsilon_0 \operatorname{div} \mathbf{E}(\mathbf{r}, t) = \rho(\mathbf{r}, t) \quad \text{Total density linked to E, external to D}$$

$$\mathbf{E}(\mathbf{r}, t) = -\operatorname{grad} \varphi(\mathbf{r}, t) \quad \text{potentials}$$

Interactions

$$\mathcal{H}_1(t) = \frac{1}{V} \sum_{\mathbf{q}} V_{\text{ext}}(\mathbf{q}, t) n(-\mathbf{q})$$

$$\epsilon_0 \nabla^2 \varphi(\mathbf{r}, t) = -\rho(\mathbf{r}, t),$$

$$\epsilon_0 \nabla^2 \varphi_{\text{ext}}(\mathbf{r}, t) = -\rho_{\text{ext}}(\mathbf{r}, t)$$

Response function: general susceptibility

$$n_{\text{ind}}(\mathbf{q}, \omega) = \tilde{\Pi}(\mathbf{q}, \omega) V(\mathbf{q}, \omega)$$

$$\Pi(\mathbf{r}, \mathbf{r}', t - t') = -\frac{i}{\hbar} \theta(t - t') \langle [n(\mathbf{r}, t), n(\mathbf{r}', t')]_- \rangle$$

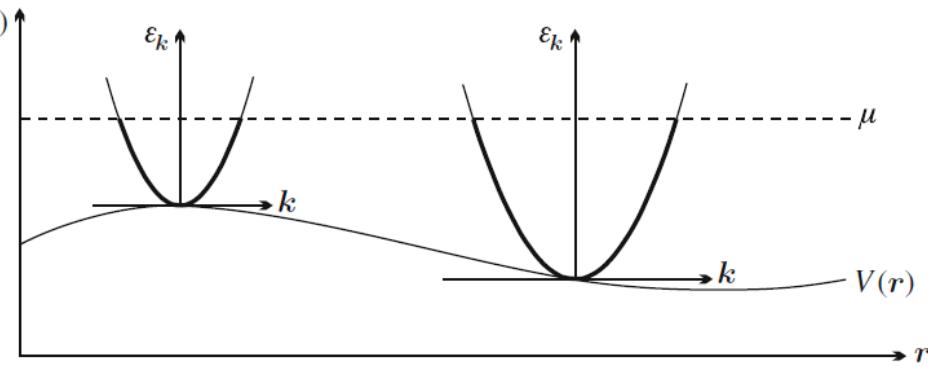
$$n_{\text{ind}}(\mathbf{q}, \omega) = \Pi(\mathbf{q}, \omega) V_{\text{ext}}(\mathbf{q}, \omega)$$

Dielectric constant

$$\Pi(\mathbf{q}, \omega) = \frac{\tilde{\Pi}(\mathbf{q}, \omega)}{1 - U(\mathbf{q}) \tilde{\Pi}(\mathbf{q}, \omega)}$$

$$\frac{1}{\epsilon_r(\mathbf{q}, \omega)} = 1 + \frac{4\pi\tilde{e}^2}{q^2} \Pi(\mathbf{q}, \omega)$$

Self consistency



$$n_{\text{ind}}(q) = -\rho(\varepsilon_F)V(q)$$

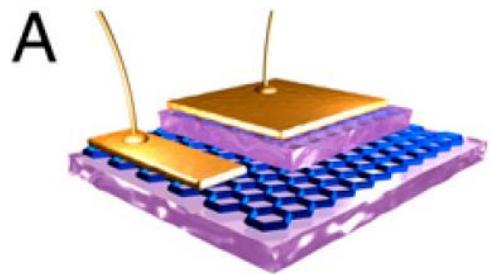
Quantum capacitance picture: takes into account long wavelength

$$\Pi_0(\mathbf{q}, \omega) = \frac{2}{V} \sum_{\mathbf{k}} \frac{f_0(\varepsilon_{\mathbf{k}}) - f_0(\varepsilon_{\mathbf{k}+\mathbf{q}})}{\hbar\omega - \varepsilon_{\mathbf{k}+\mathbf{q}} + \varepsilon_{\mathbf{k}} + i\delta}$$

Lindhard picture

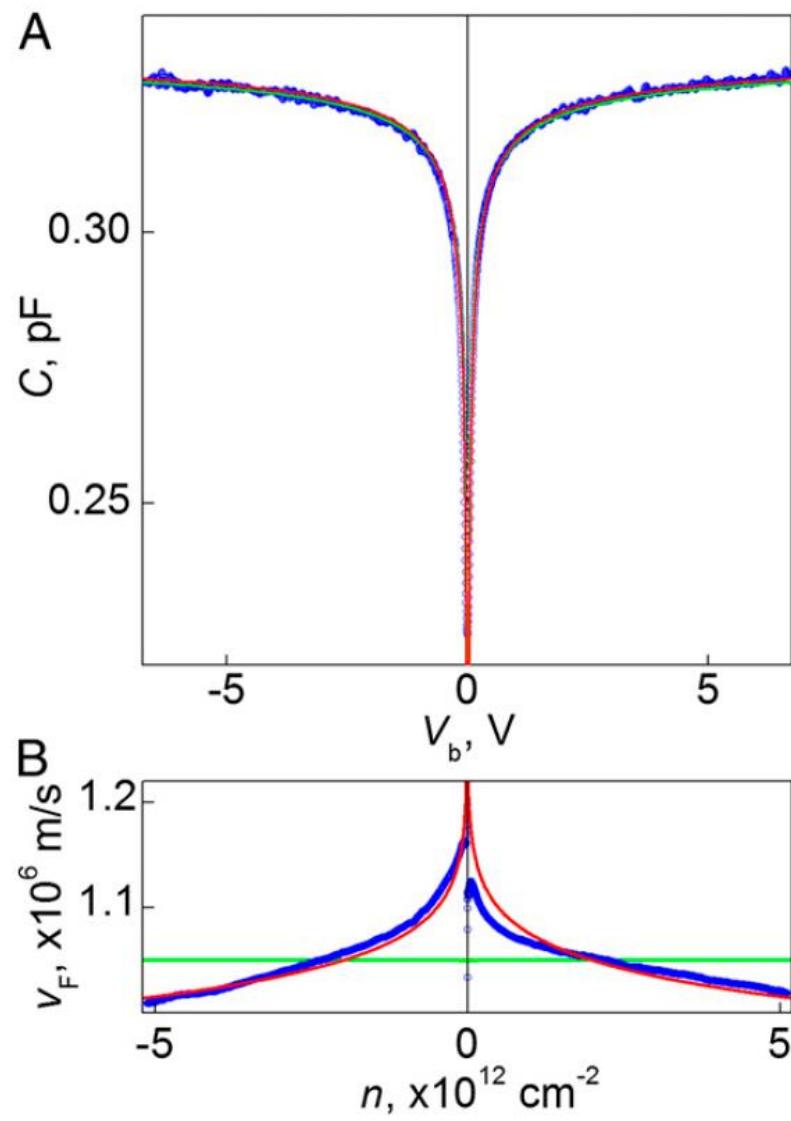
$$\Pi(\mathbf{q}, \omega) = \frac{\tilde{\Pi}(\mathbf{q}, \omega)}{1 - U(\mathbf{q})\tilde{\Pi}(\mathbf{q}, \omega)}$$

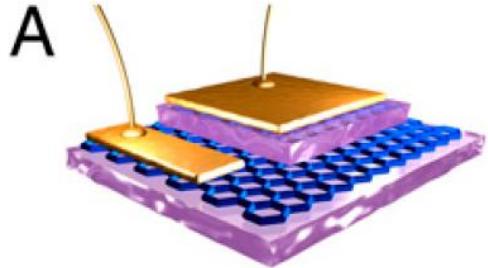
$$n = C_g V_g = \frac{C_g \cdot C_Q}{C_g + C_Q} V_g = \frac{C_Q}{\frac{C_Q}{C_g} + 1}$$



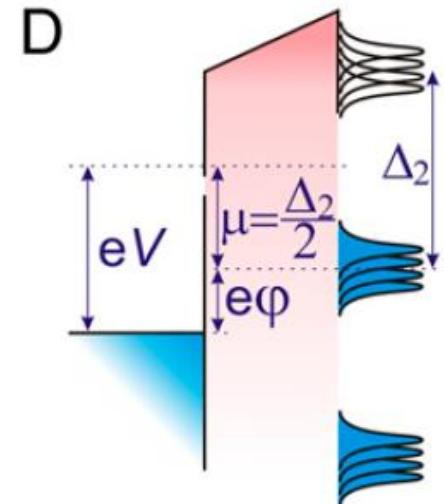
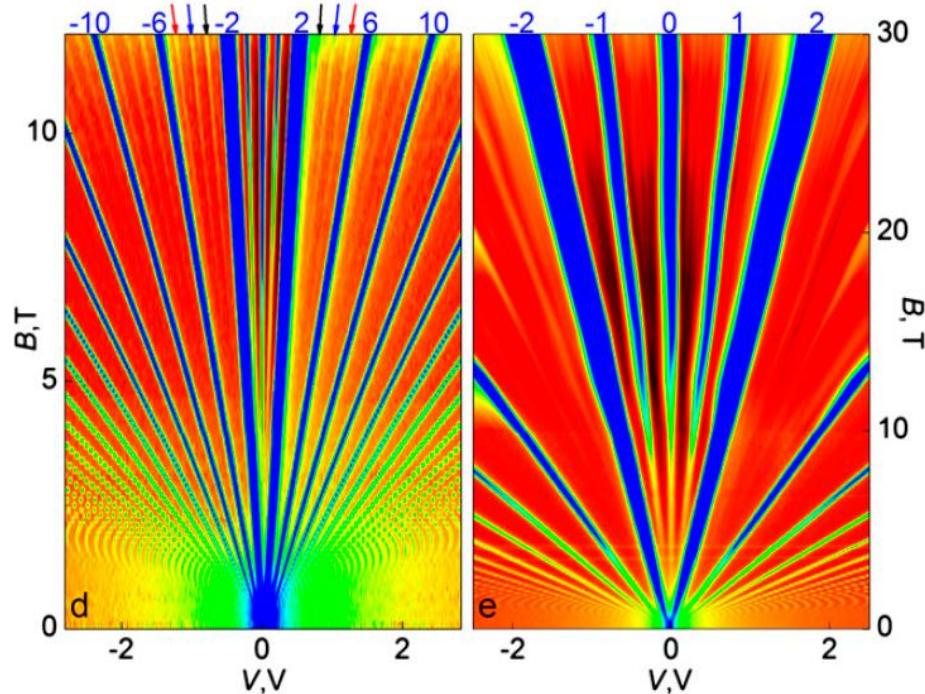
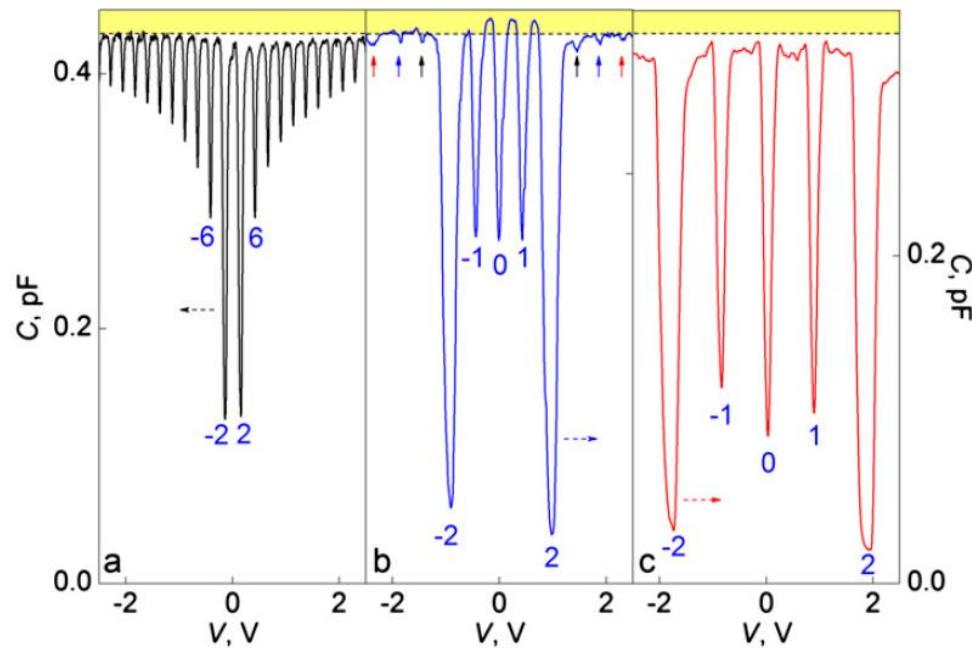
$$v_F(n) = v_F(n_0) \left[1 + e^2 \cdot \ln(n_0/n) / 16\hbar\varepsilon_0\varepsilon v_F(n_0) \right]$$

Electron-electron interaction renormalizes vf





Quantum Hall regime: when bulk is gapped capacitance is zero.
Can be tested if the bulk is gapped.



$$\kappa^{-1} = n^2 d\mu/dn$$

Inverse compressibility

$$\kappa \sim D_0$$

compressibility

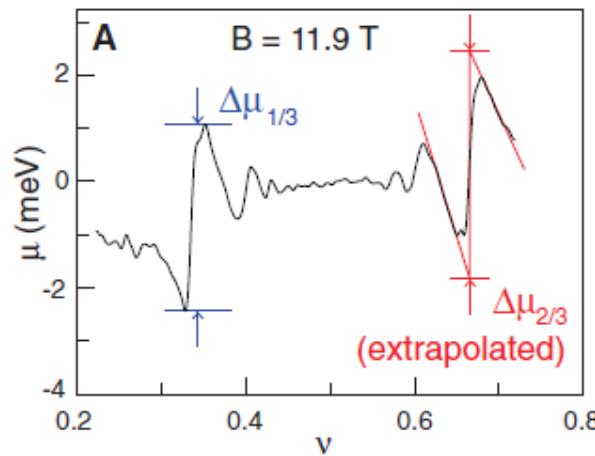
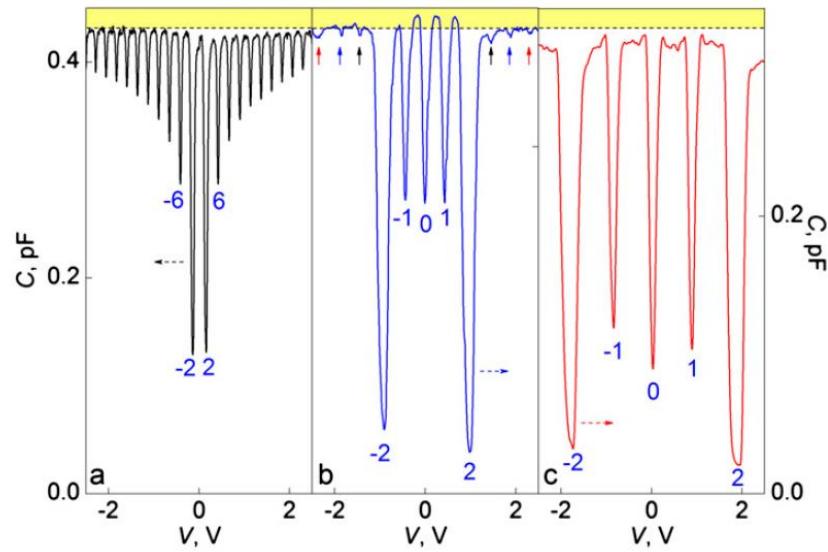
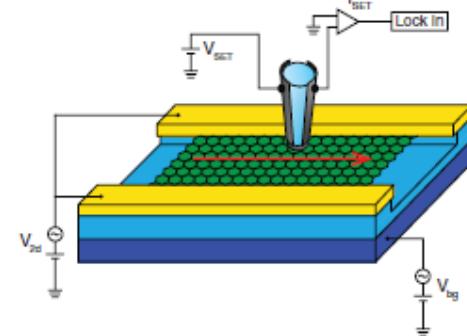
Dips: incompressible state

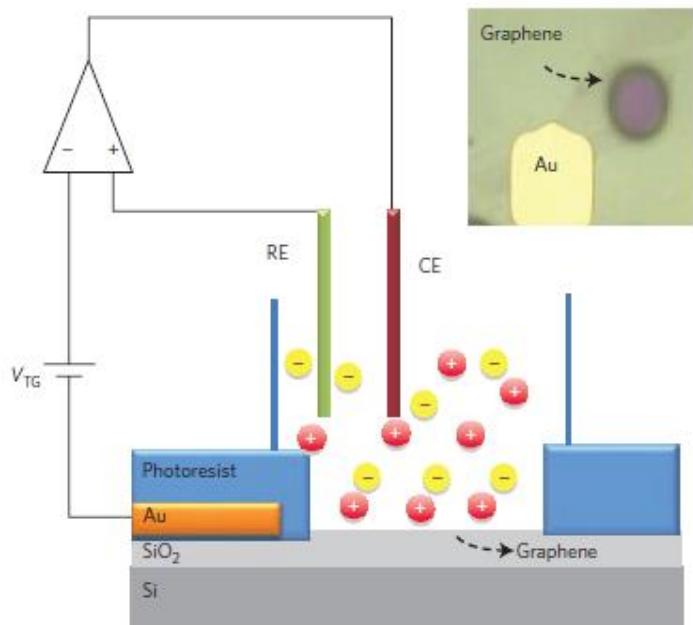
Gapped state:

Chemical potential can be increased without adding charges

Compressible state

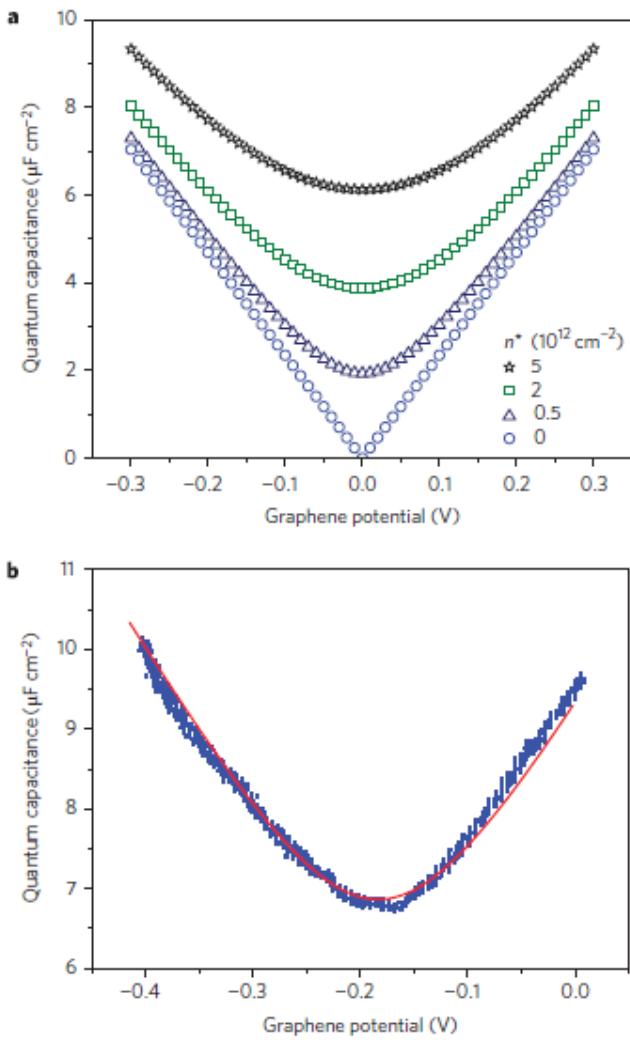
On LL: you have to add charges to increase chemical potential

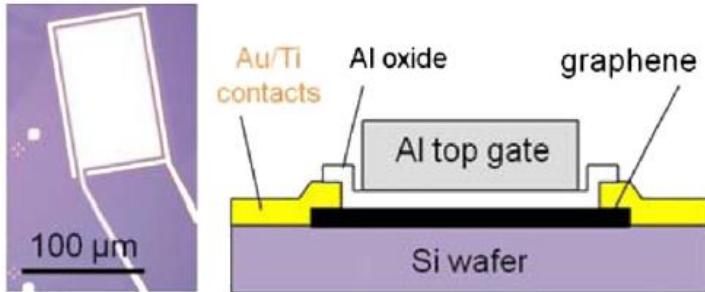




Using a liquid gate quantum capacitance dominates

$$C_Q = \frac{2e^2}{\hbar v_F \sqrt{\pi}} (|n_G| + |n^*|)^{1/2}$$



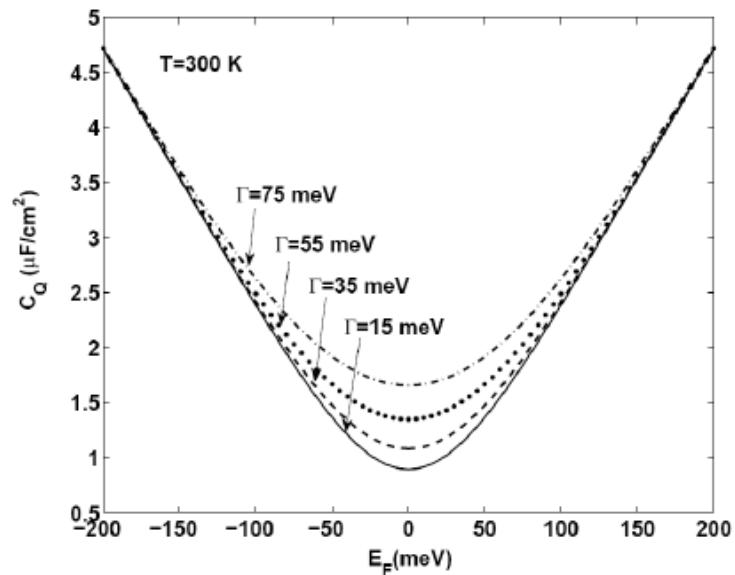
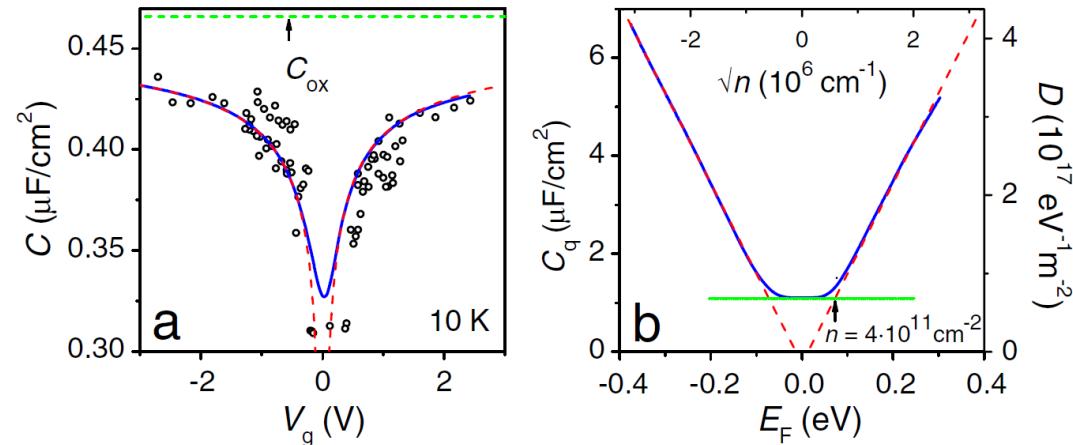


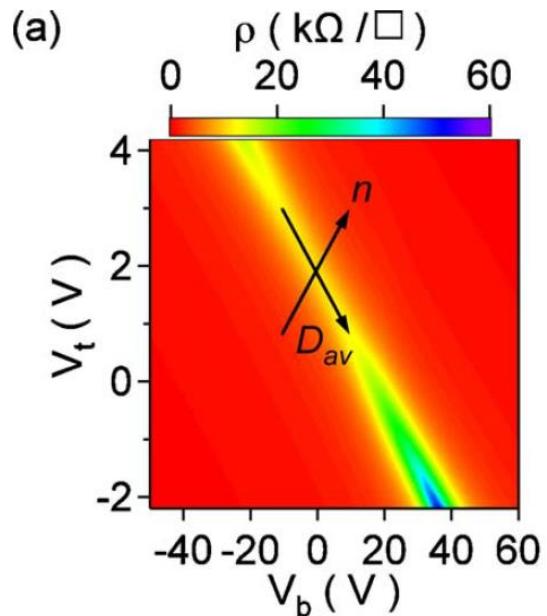
Using a topgate capacitance

$$C_Q = \frac{2e^2}{\hbar v_F \sqrt{\pi}} (|n_G| + |n^*|)^{1/2}$$

Sometimes smearing of DOS is introduced (e.g. puddles):

$$D(E) = \frac{1}{\sqrt{2\pi}\Gamma} \int_{-\infty}^{+\infty} \exp\left(-\frac{(\varepsilon - E)^2}{2\Gamma^2}\right) g(\varepsilon) d\varepsilon$$



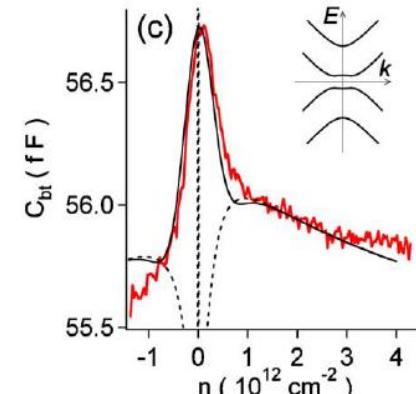
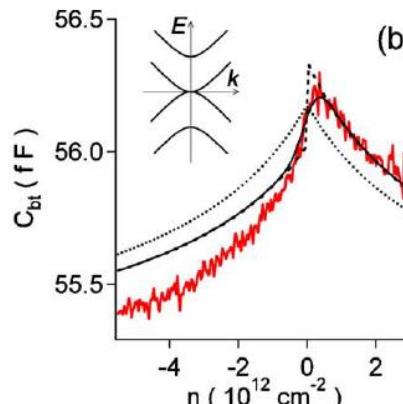
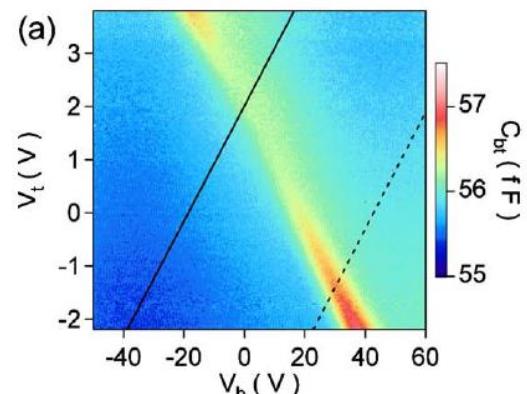
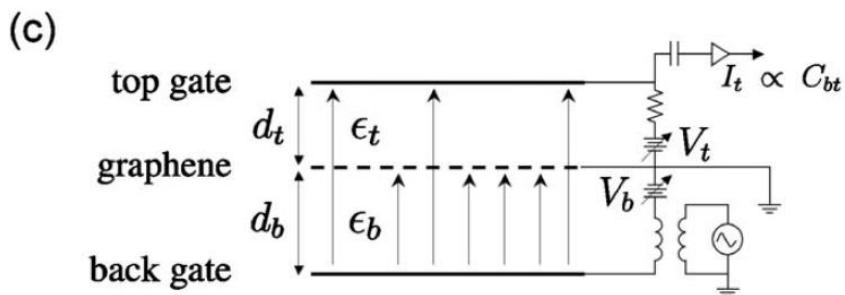


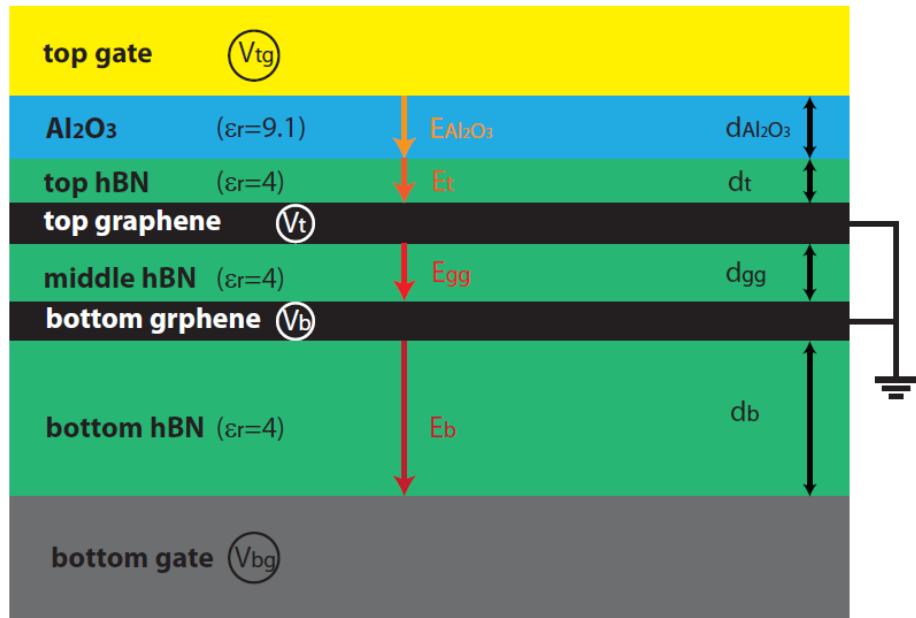
(b)

$$C_{bt} = \frac{A_t d_g \epsilon_b \epsilon_t}{d_g (\epsilon_t d_b + \epsilon_b d_t) + \epsilon_0 d_b d_t} + C_s.$$

$$d_g = (\epsilon_0 / e^2) \partial \mu / \partial n,$$

Bilayer graphene – measure penetration capacitance:





$$\mu_c^t + eV_t = \mu_c^b + eV_b = 0,$$

$$\mu_c = sgn(n)\hbar v_F \sqrt{\pi|n|},$$

$$en_t = \epsilon_0 \epsilon_r^{hBN} (E_{gg} - E_t)$$

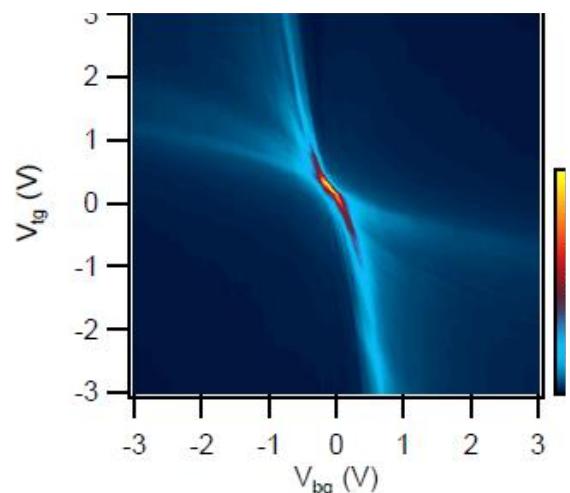
$$en_b = \epsilon_0 \epsilon_r^{hBN} (E_b - E_{gg})$$

$$E_b d_b = V_b - V_{bg}$$

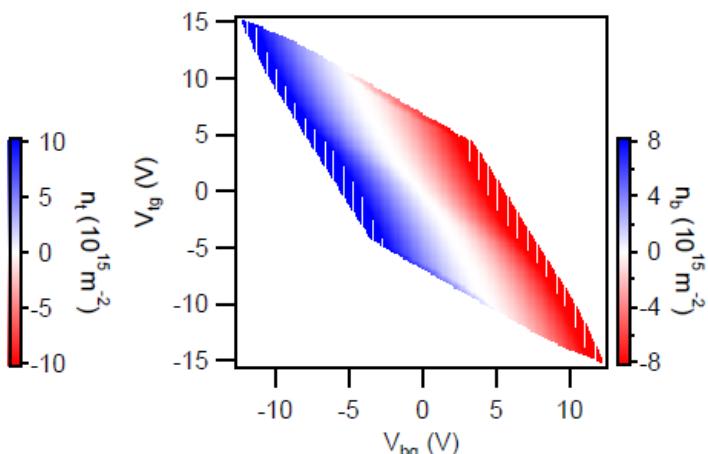
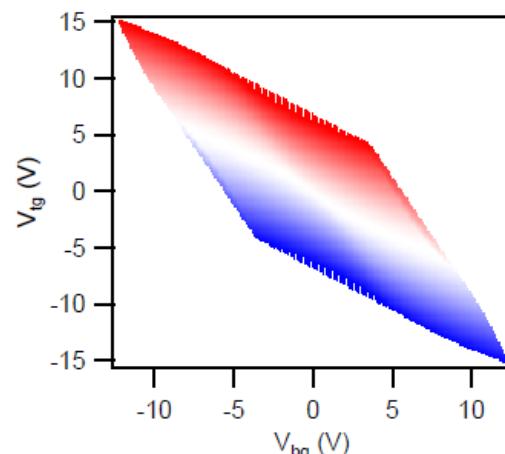
$$E_{gg} d_{gg} = V_t - V_b$$

$$E_t d_t + E_{Al2O3} d_{Al2O3} = V_{tg} - V_t$$

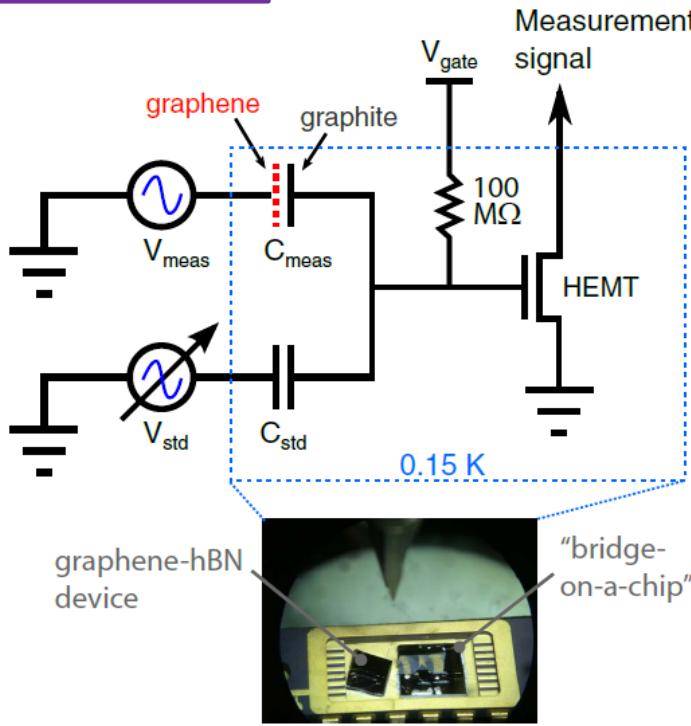
$$V_{tg} = -\frac{sgn(n_t)\sqrt{\pi}\hbar v_F}{e}\sqrt{|n_t|} - \frac{en_t d_t^{eff}}{\epsilon_0 \epsilon_r^{hBN}} - \frac{\sqrt{\pi}\hbar v_F d_t^{eff}}{ed_{gg}} \left(sgn(n_t)\sqrt{|n_t|} - sgn(n_b)\sqrt{|n_b|} \right).$$



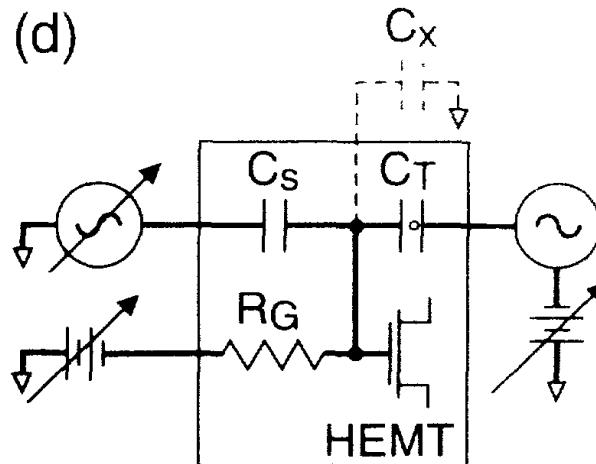
D. Indolese



Methods



(d)



Idea: Capacitance bridge
Measure only the change in capacitance.

Capacitance change is sensed by the HEMT (in AC).

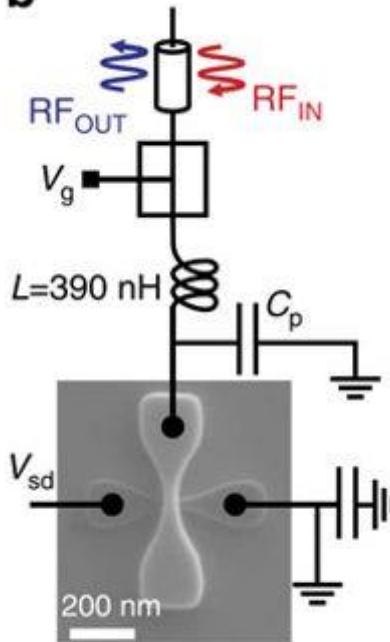
First at a particular gate voltage the bridge is balanced by changing V_{std} :

$$C_{meas} = (V_{std}/V_{meas}) C_{std}$$

Also care has to be taken, since if the sample gaps time constants become long....

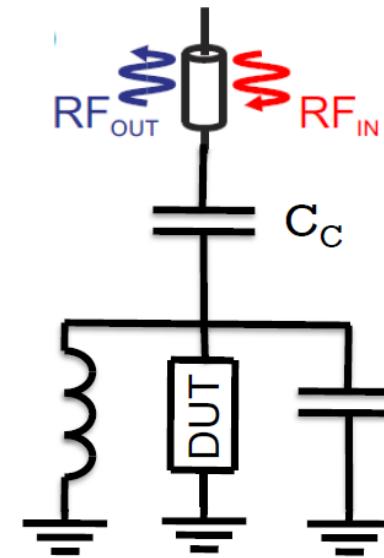
Methods

b

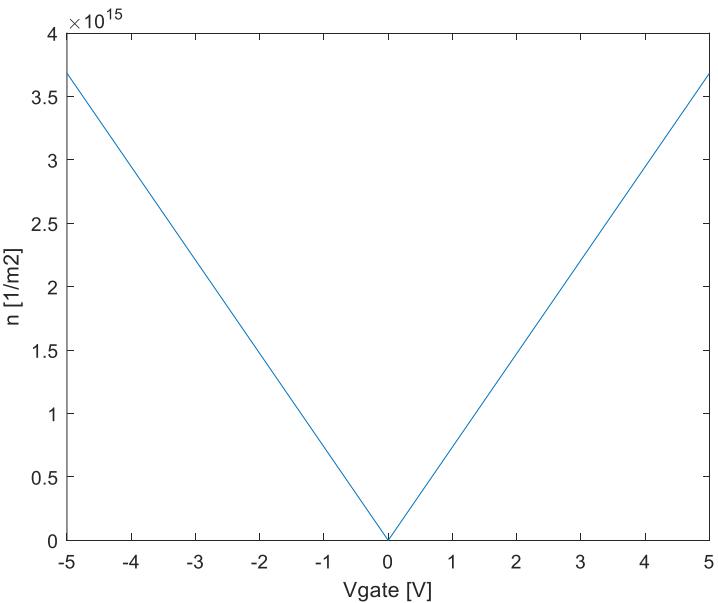
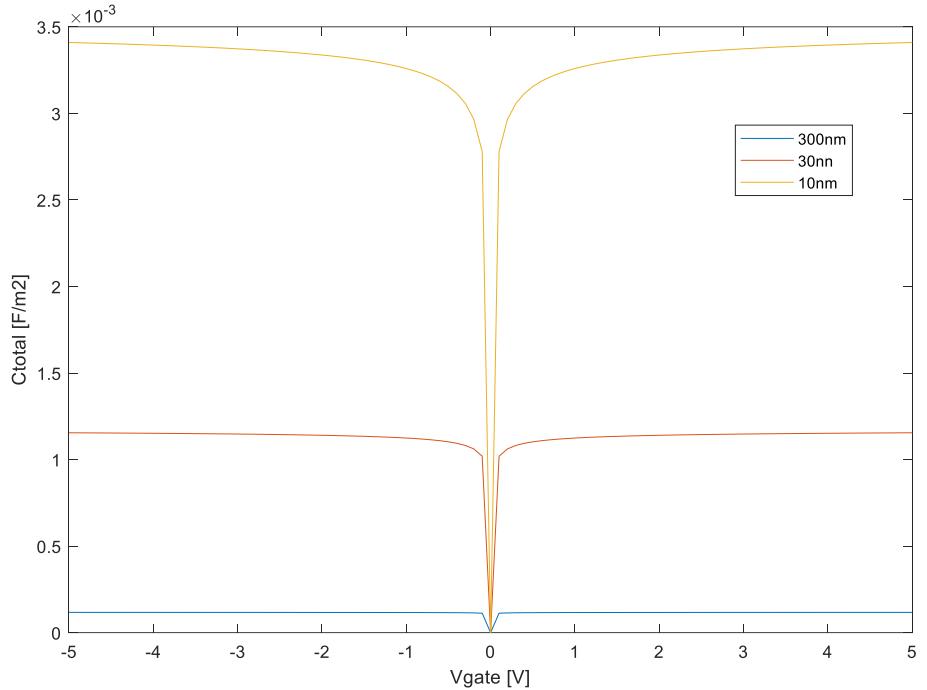


Reflectometry? Not often used for 2D systems
Gate reflectometry
Challenge:
Reduce parallel capacitance

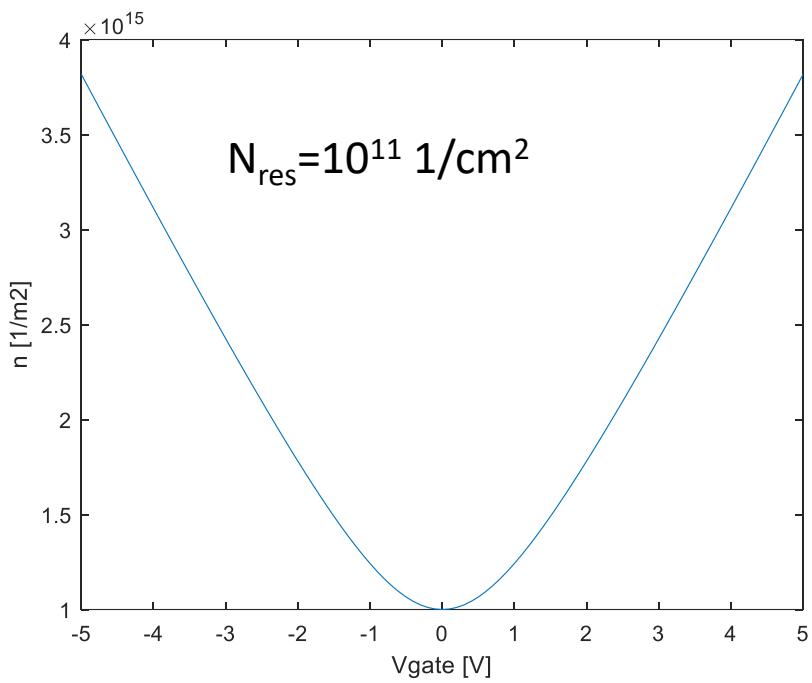
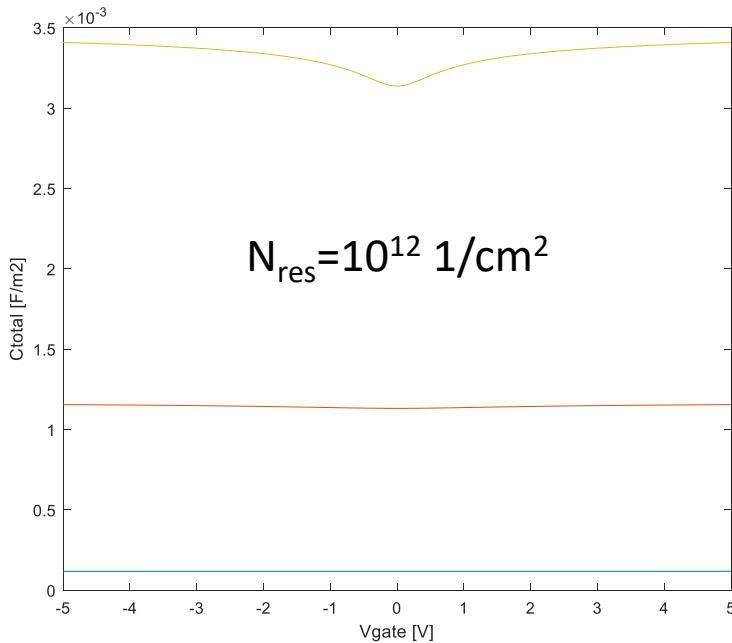
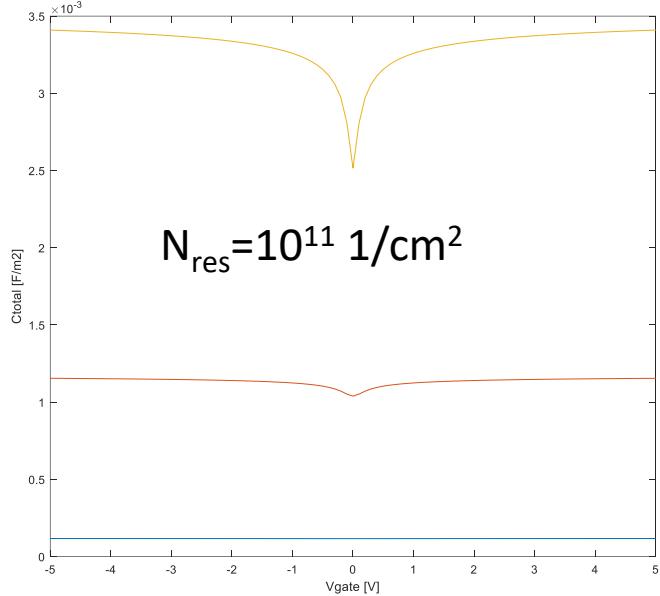
- Parallel resonator



Some calculation SLG

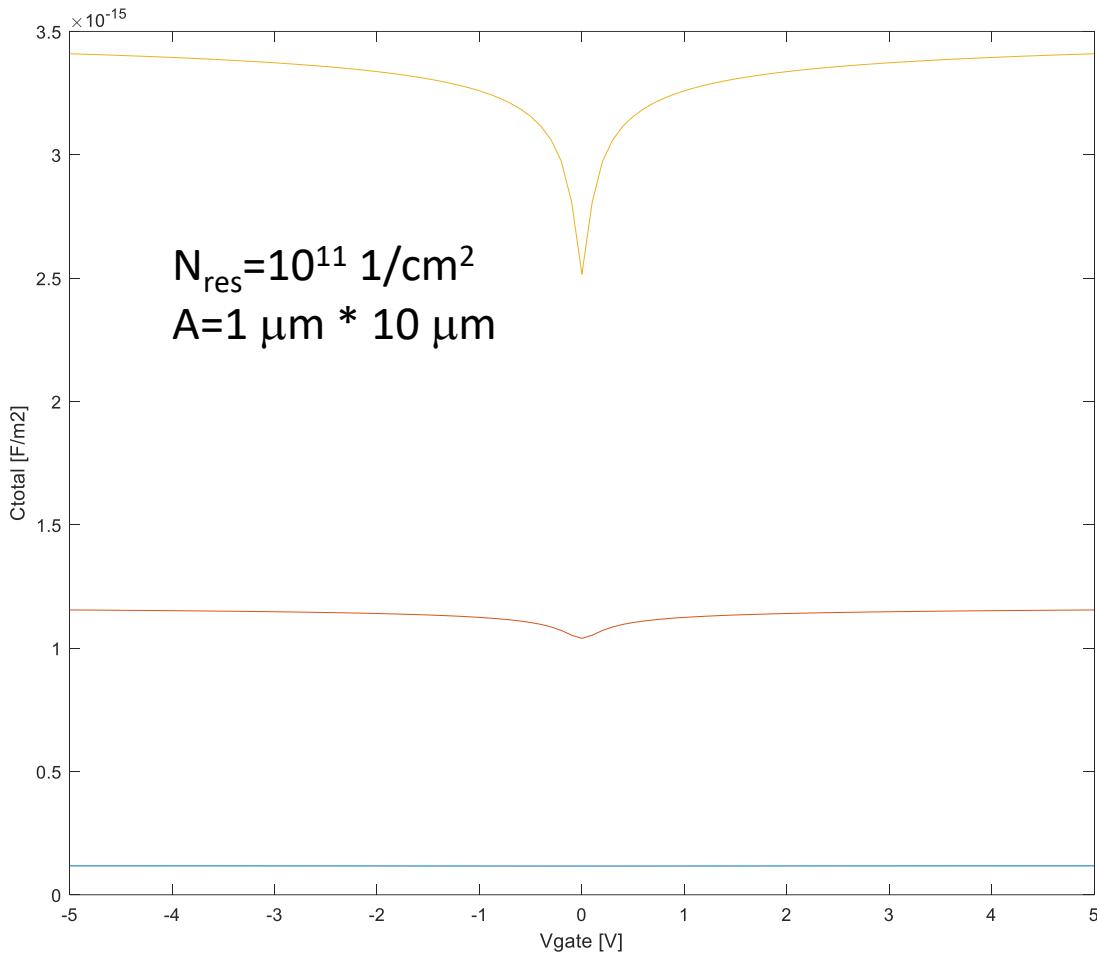


Some calculation SLG

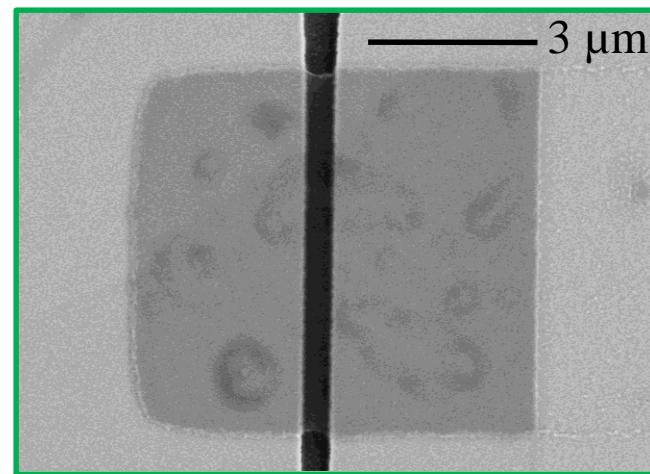
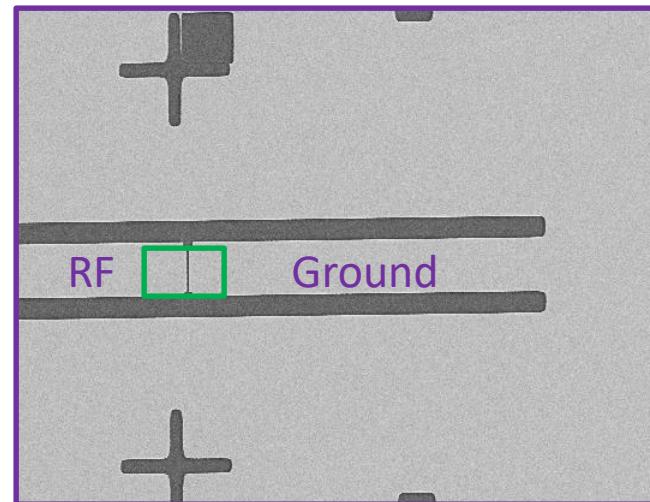
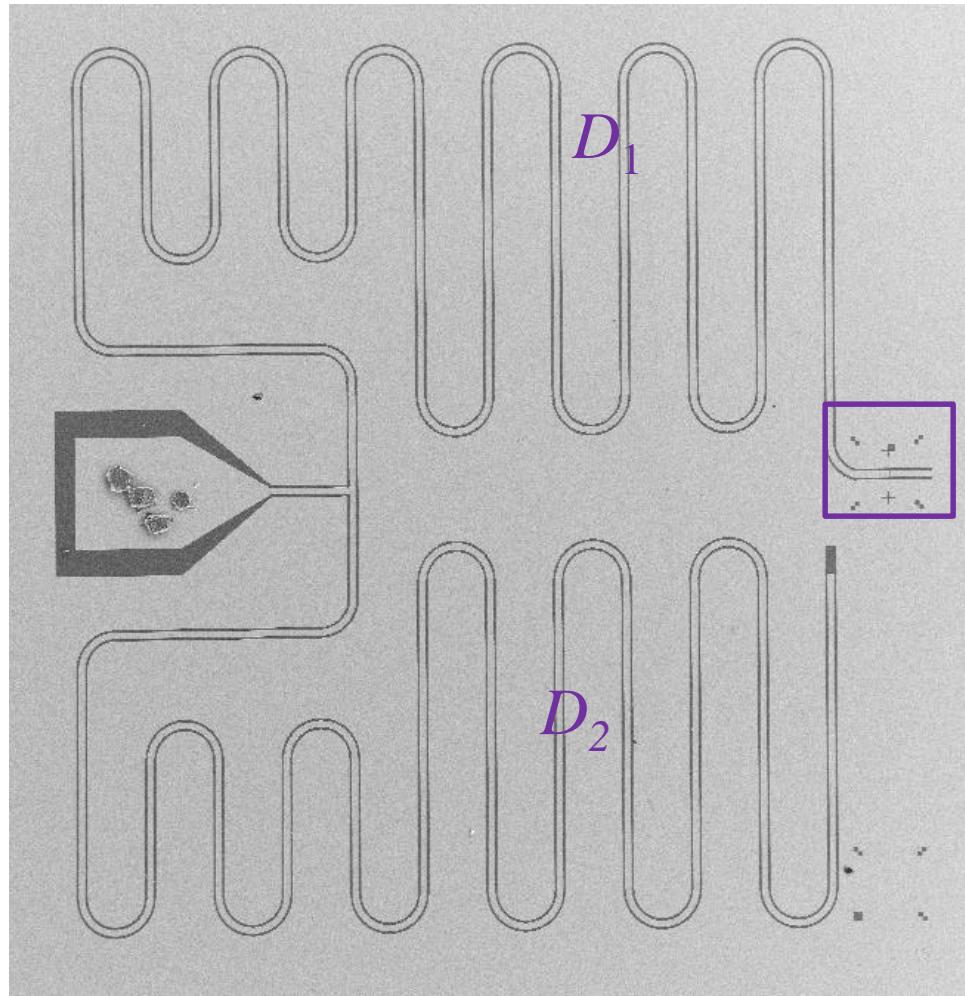


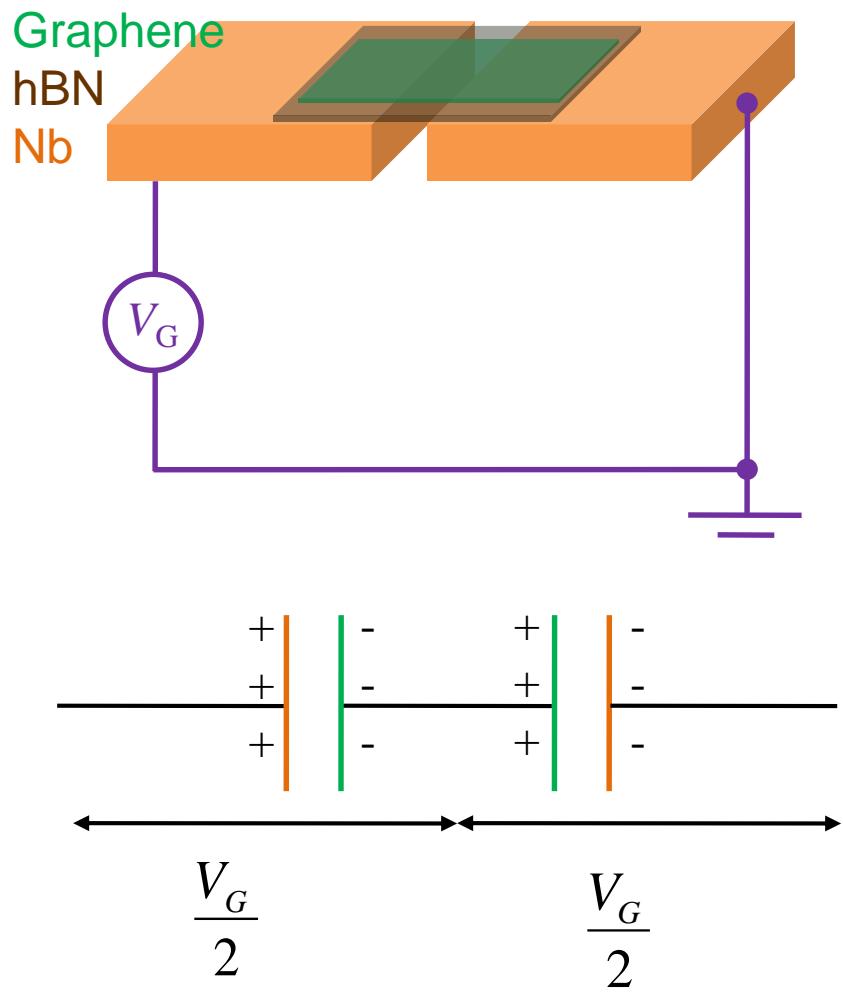
Some calculation

SLG

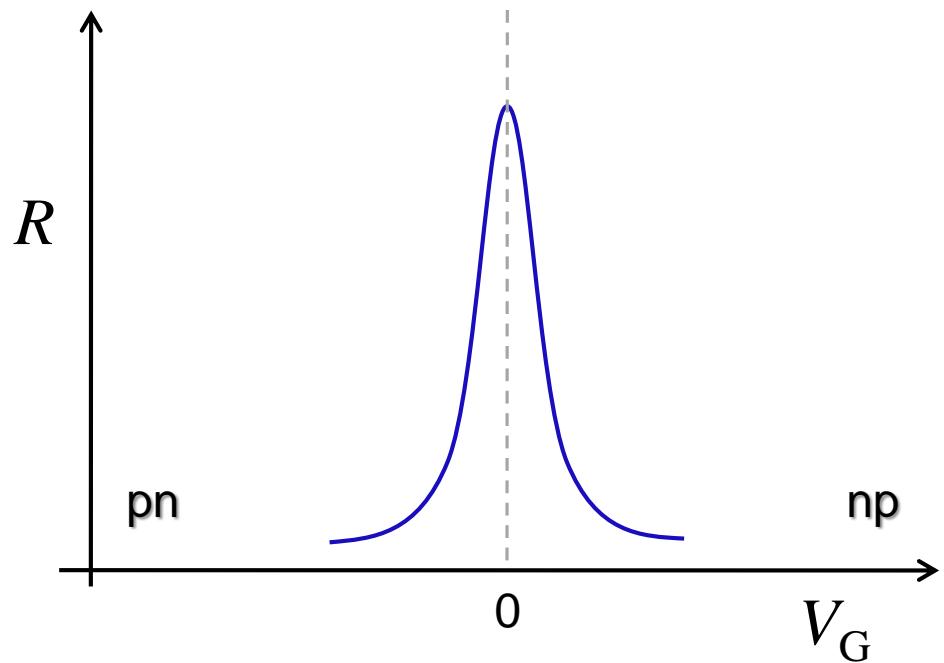


Pn measurement

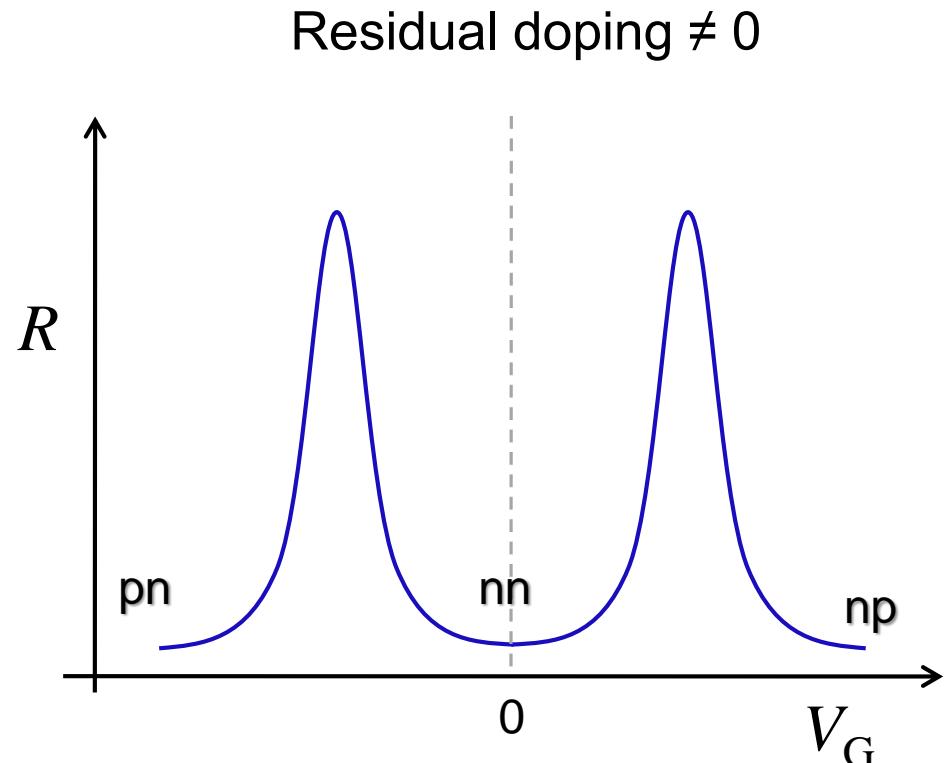
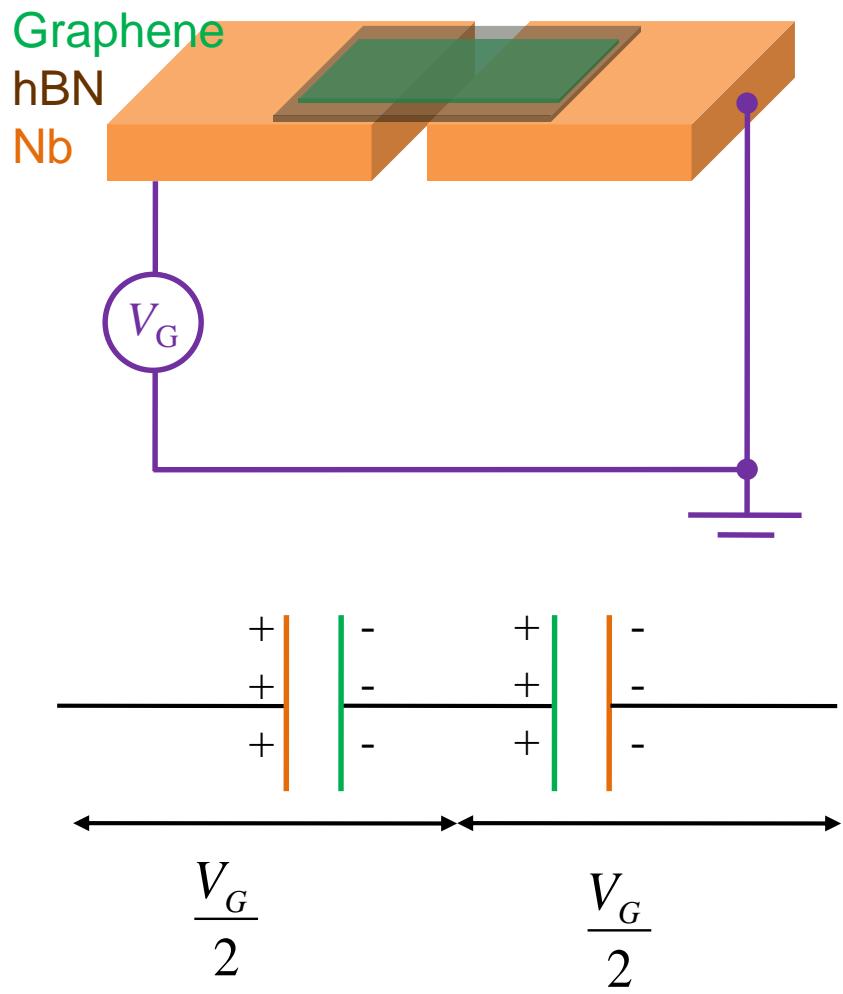




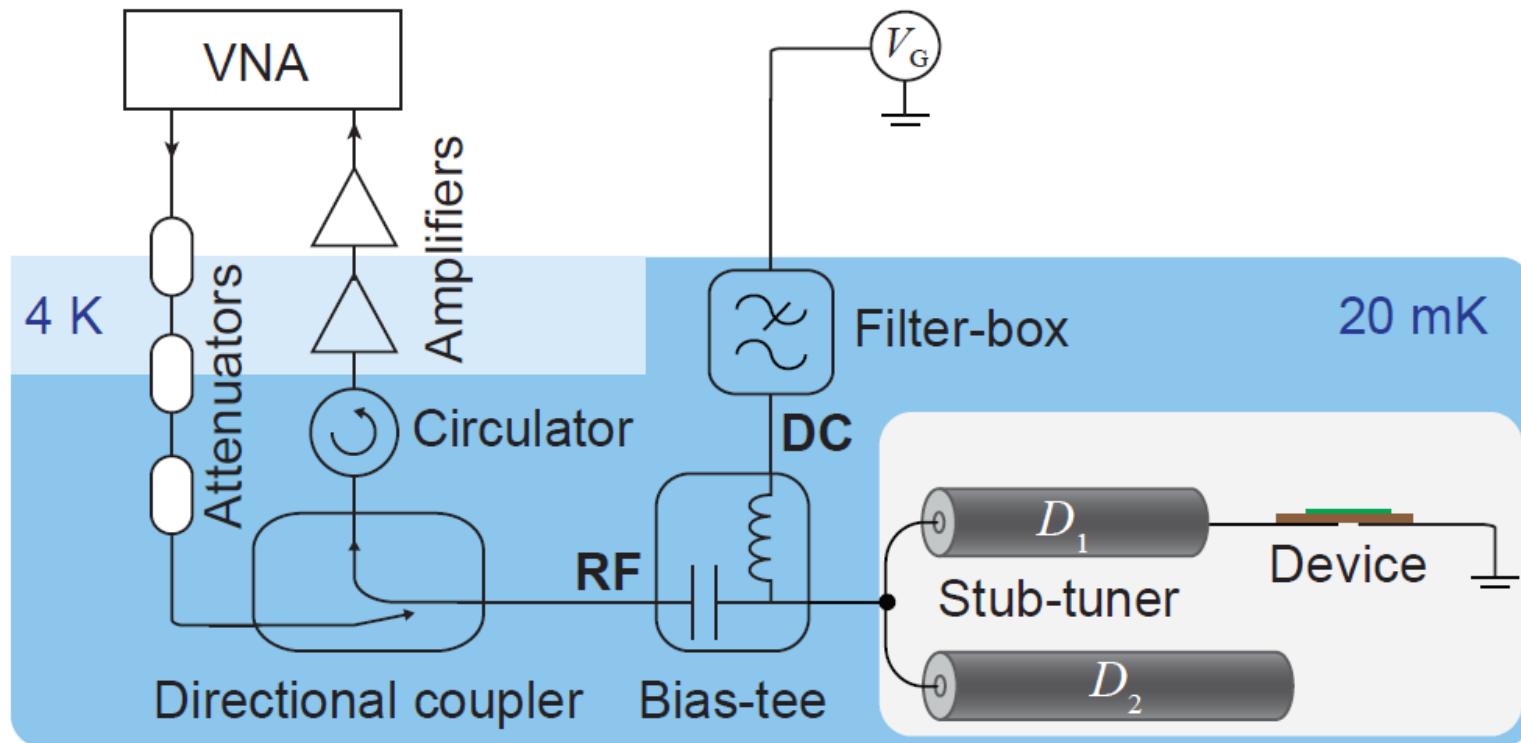
Residual doping = 0

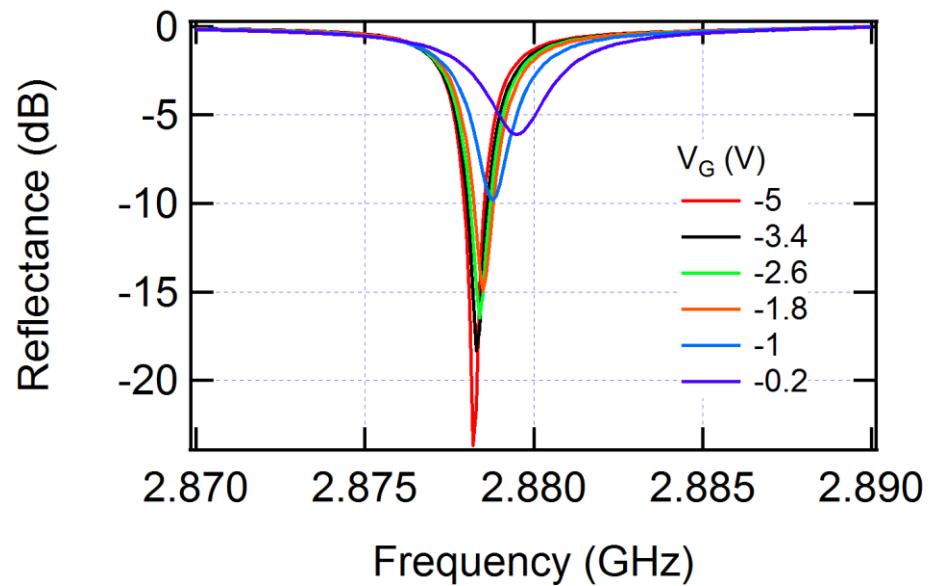
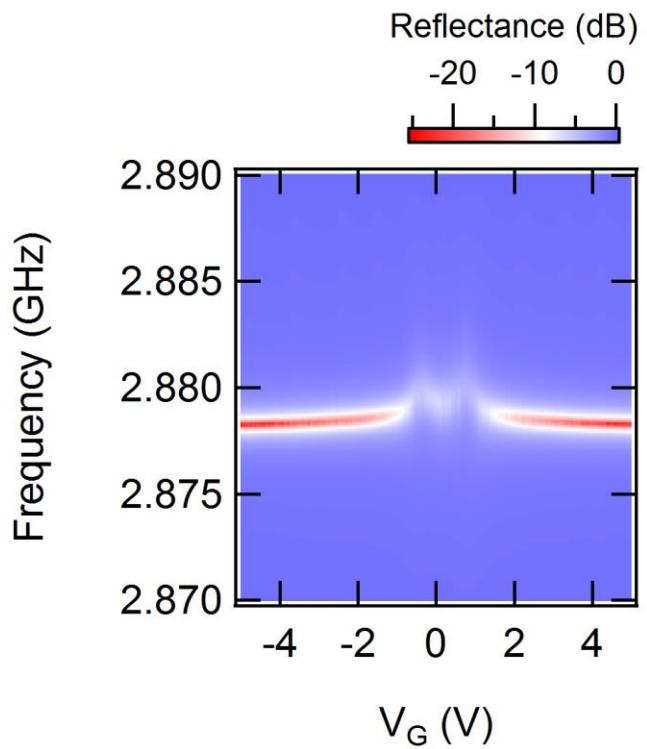


Symmetric graphene

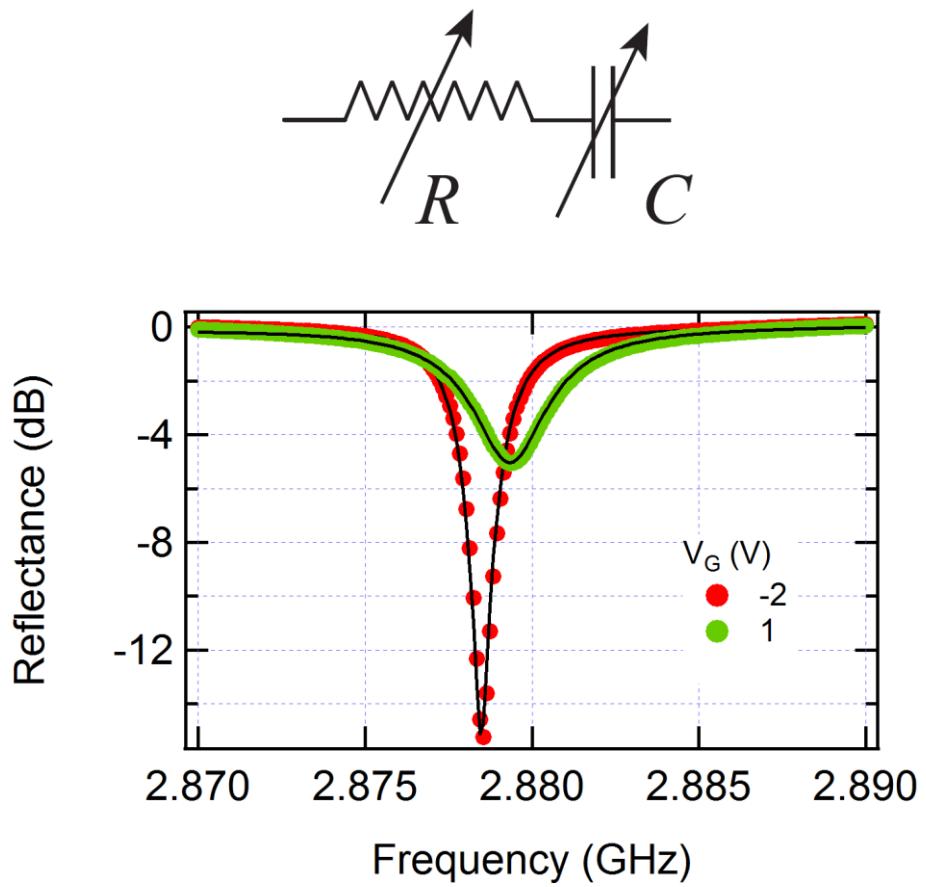
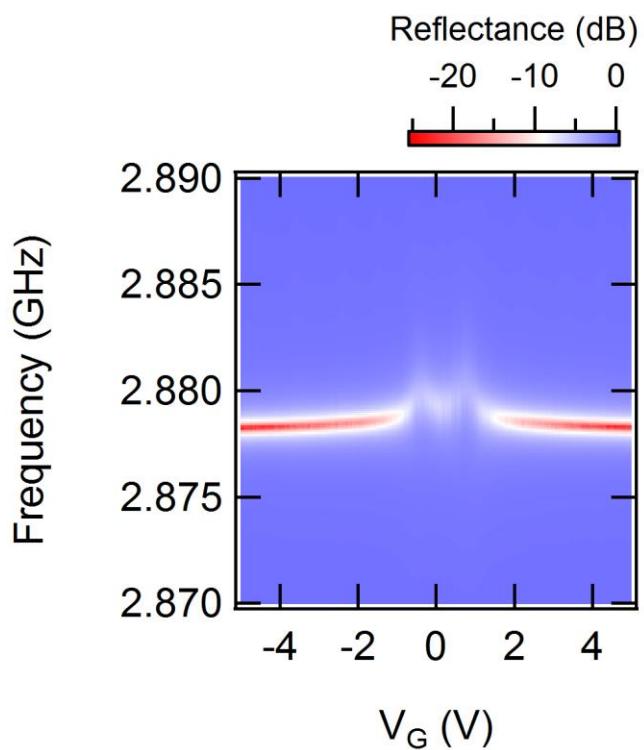


Symmetric graphene





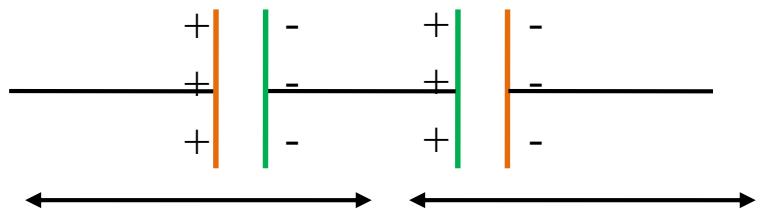
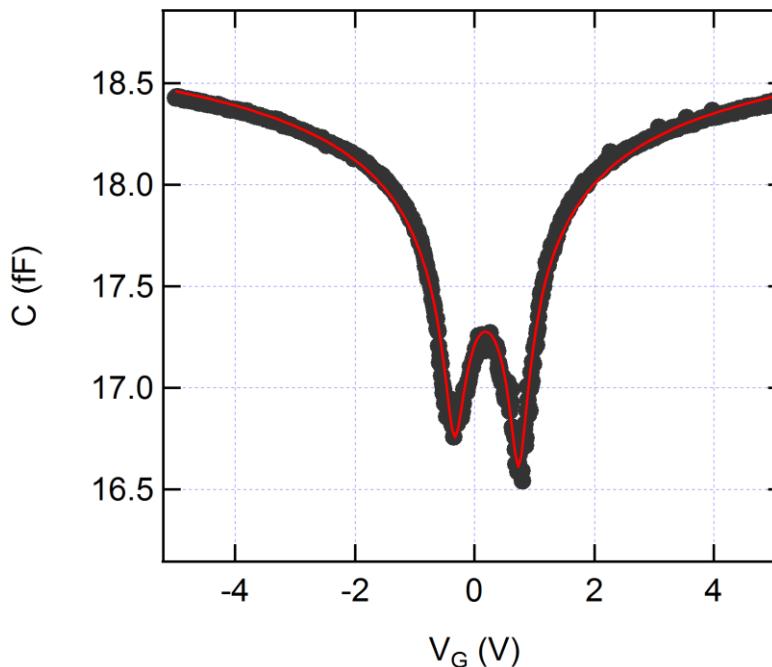
Frequency shifts and linewidth changes
due to varying capacitance and resistance



$$Z_{in} = Z_0 \left[\tanh(\gamma D_2) + \frac{Z_0 + Z_L \tanh(\gamma D_1)}{Z_L + Z_0 \tanh(\gamma D_2)} \right]$$

$$\begin{aligned} R &= 94.9 \Omega & R &= 263.1 \Omega \\ C &= 19.8 \text{ fF} & C &= 18.8 \text{ fF} \end{aligned}$$

$$Z_L = R + \frac{1}{j\omega C}$$



$$\frac{V_G}{2}$$

$$\frac{V_G}{2}$$

$$C_q = \frac{2e^2 A}{\hbar v_F \sqrt{\pi}} \sqrt{n_{tot}}$$

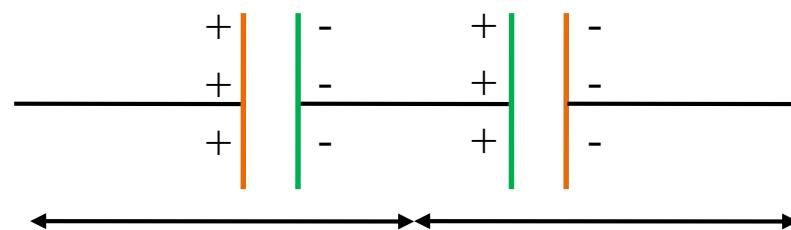
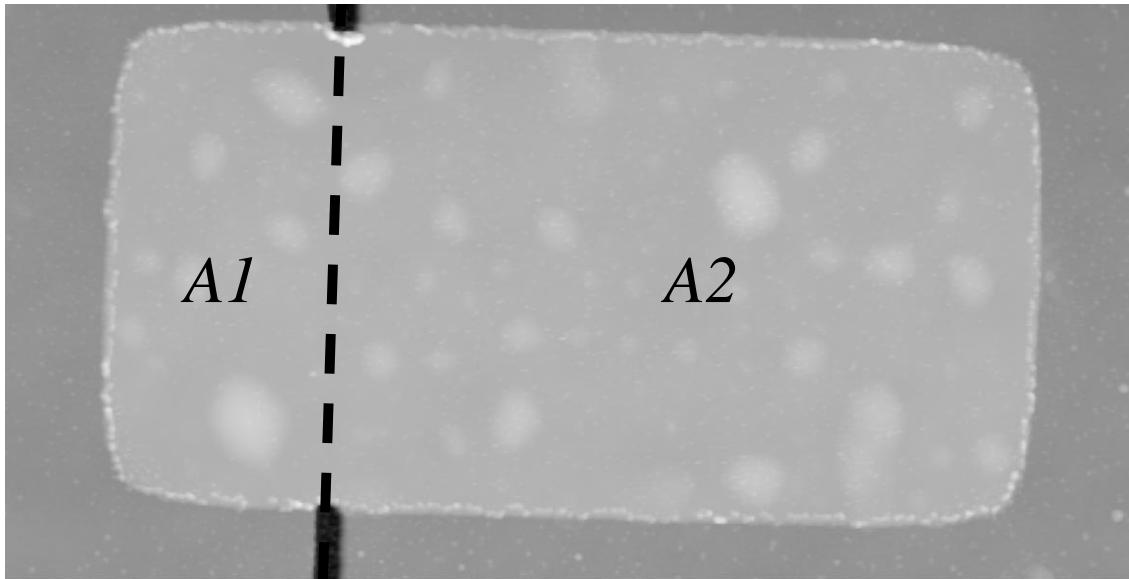
$$n_{tot} = \sqrt{n^2 + n_{imp}^2}$$

$$n = \frac{C_g (V_G - V_D)}{A e}$$

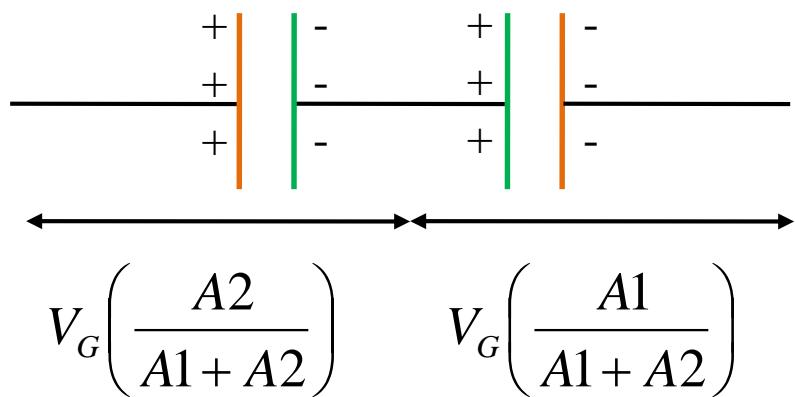
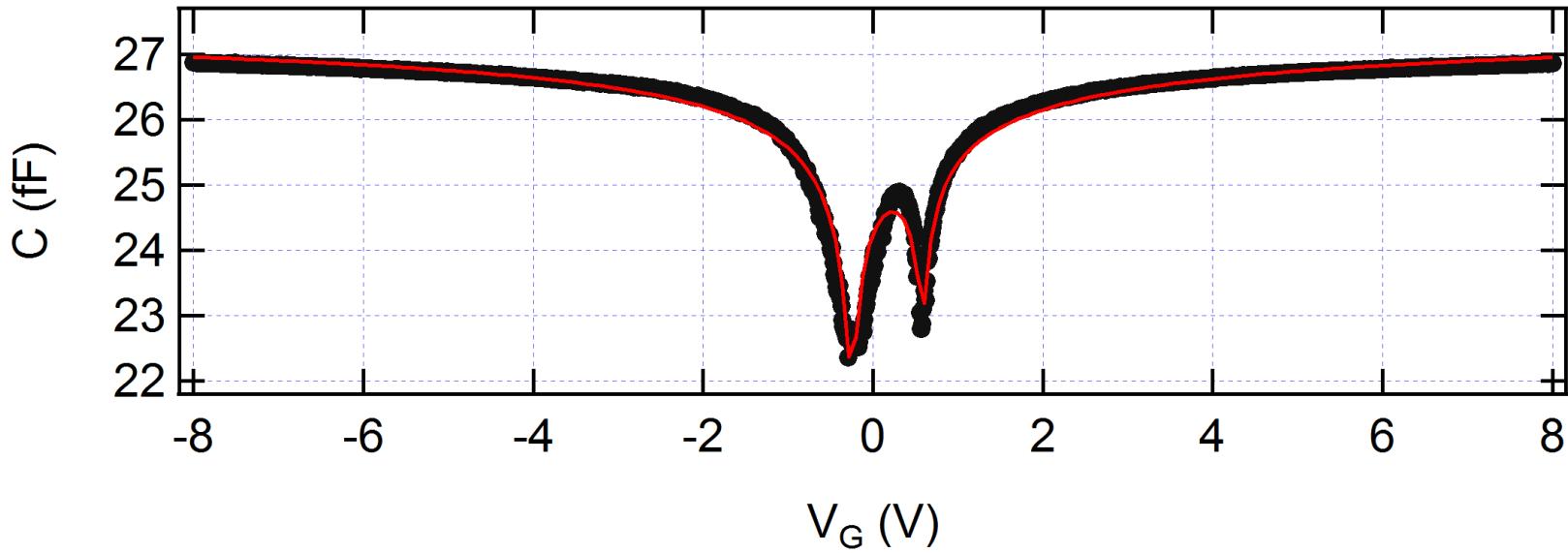
$$n_{imp} \approx 6 \times 10^{10} \text{ cm}^{-2}$$

$$v_F \approx 0.95 \times 10^6 \text{ m/s}$$

$$\epsilon_{BN} \approx 4$$



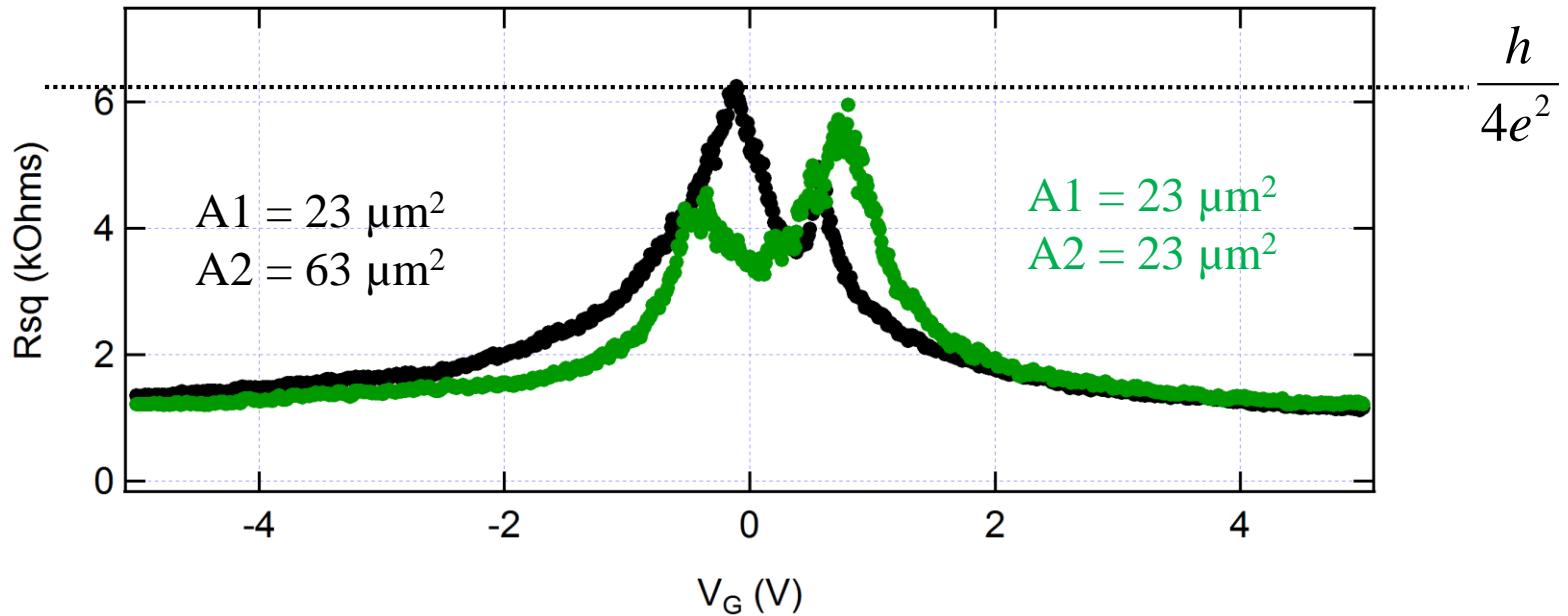
$$V_G \left(\frac{A2}{A1 + A2} \right) \quad V_G \left(\frac{A1}{A1 + A2} \right)$$



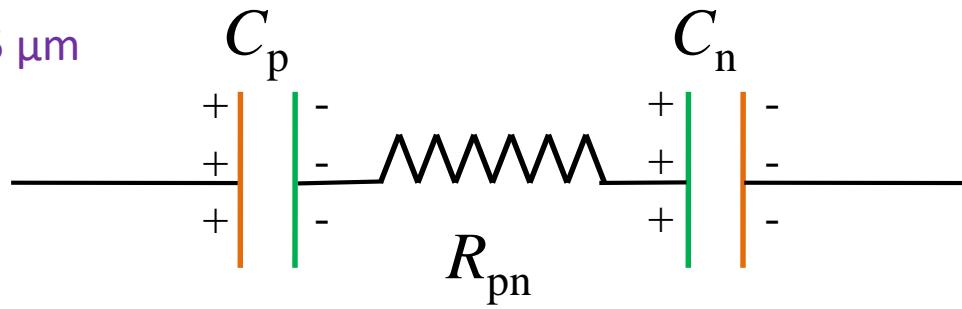
$$n_{imp} \approx 3 \times 10^{10} \text{ cm}^{-2}$$

$$v_F \approx 1.03 \times 10^6 \text{ m/s}$$

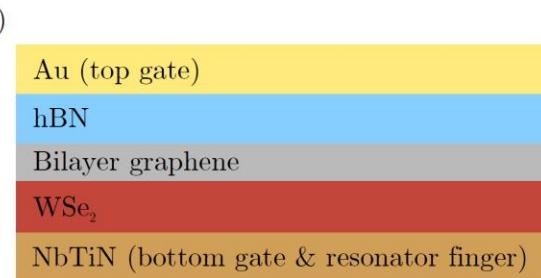
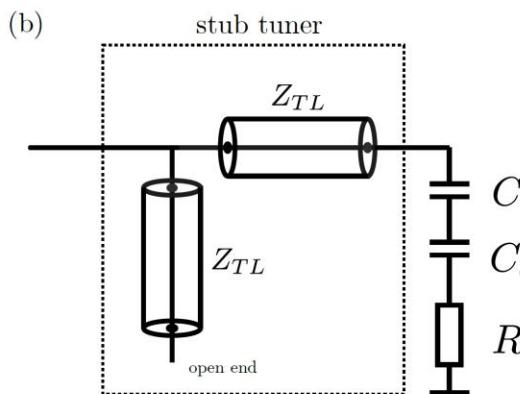
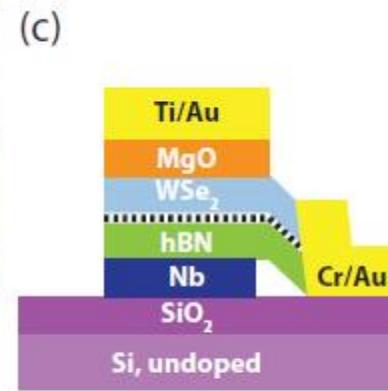
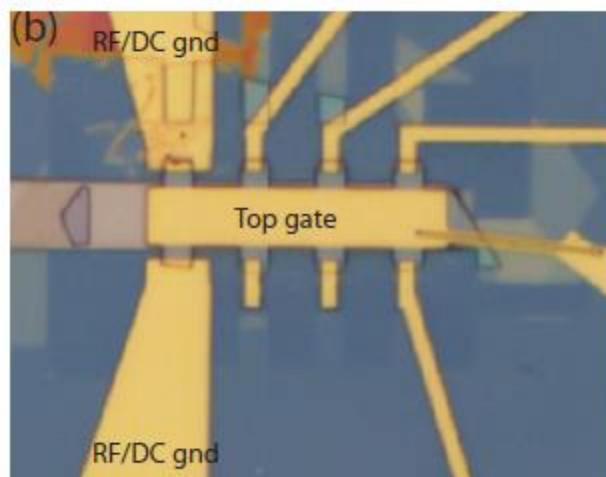
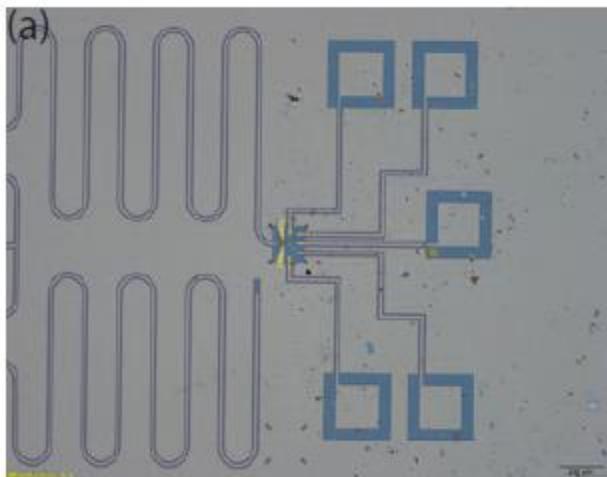
$$\mathcal{E}_{BN} \approx 4$$



Slit width = 400 nm
Graphene width = 6.5 μm

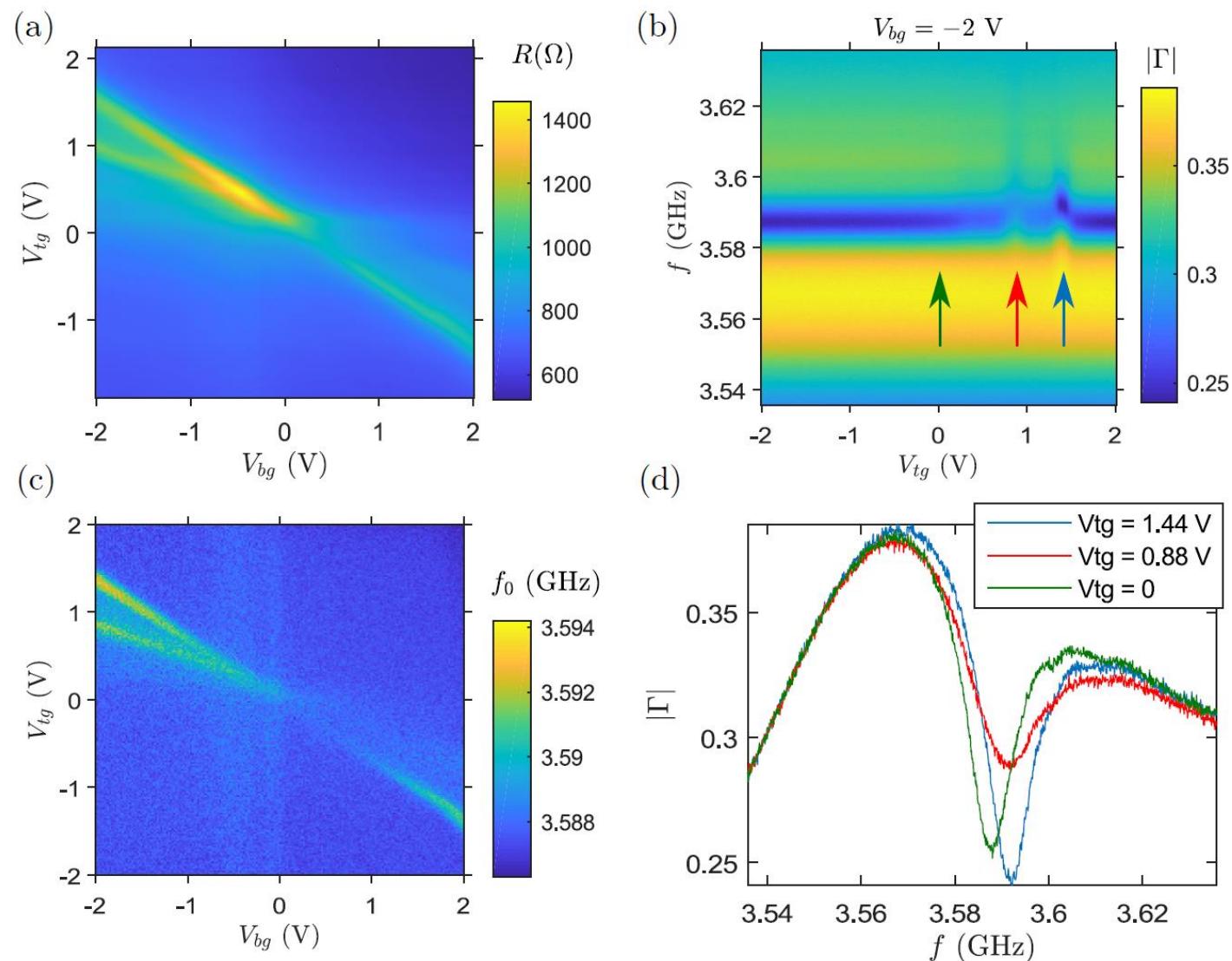


Capacitance measurements



- Couple it to SC resonator to measure DOS
- Quantum capacitance shifts the resonance frequency of the resonator

Capacitance measurements



- See E-field induced gap

DOTS?



$$\alpha_G = \frac{\Delta\mu}{|e|\Delta V_G} = \frac{C_G}{C_\Sigma}.$$

$$\alpha_G = \frac{C_G}{C_\Sigma} = \frac{\beta^+ |\beta^-|}{\beta^+ + |\beta^-|},$$

$$\beta^- = -\frac{C_G}{C_S} \quad \text{and} \quad \beta^+ = \frac{C_G}{C_\Sigma - C_S},$$

